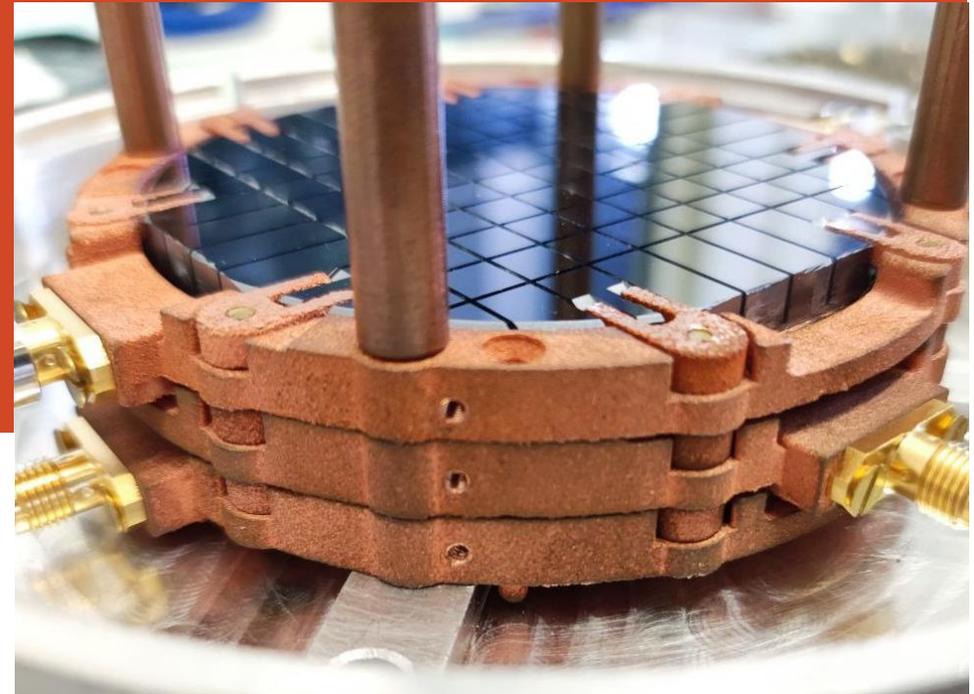


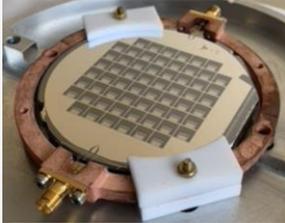
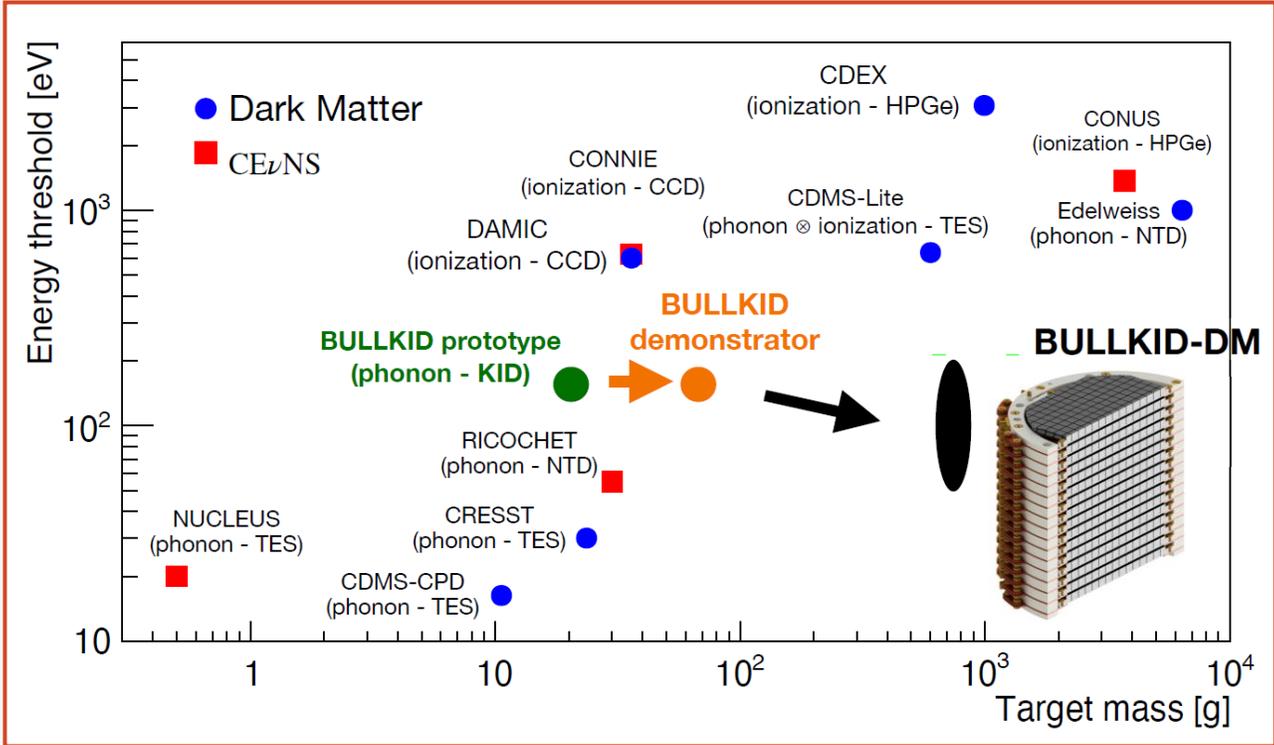
Surface background with mild shield: an update from the demonstrator

01/07/2025 – BULLKID-DM Meeting – Ferrara

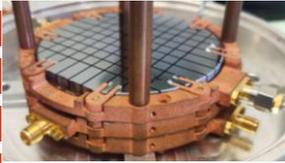
Daniele Delicato on behalf of the collaboration



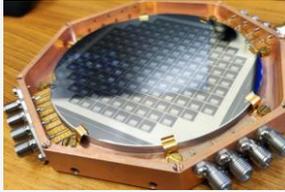
Status of the BULLKID 3" demonstrator



Prototype - 20 g / 60 dice
single 3" wafer
concluded in 2023



Demonstrator - 60 g / 180 dice
3-layer stack of 3" wafers
operations ongoing

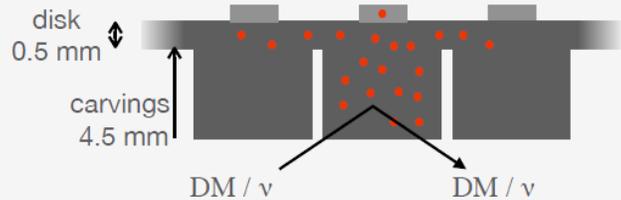


R&D on large wafer 50 g / 145 dice
single 100 mm wafer first operations
fall 2024



BULLKID-DM - 800 g / 2300 dice
16-layer stack of 100 mm wafers
commissioning in 2026 at Sapienza U.
Fiducial mass: 600g

- Threshold (ongoing R&Ds):
1. Replace Al with Al-Ti-Al KIDs: 5x inductance
 2. Deeper carvings for higher phonon focussing



Status of the BULLKID 3" demonstrator*

***as of, 16/01/25**

- **Thermalization** of the wafers via the copper structure
- **Electrical coupling** not compromised by proximity among wafers
- **Energy threshold** on par with earlier prototypes
- **Scale readout and analysis** to simultaneously measure multiple wafers
- **Background** in a shielded environment **flat and lower than 10^5 dru**



From the CDR:

For the time being we plan to repeat the measurement with a mild lead shield at Sapienza U. before the end of the year (the maximum amount of lead is limited to a few kg by the load that the current cryostat can sustain). This shield is expected to reduce the background by a factor close to 50, below 10^5 DRU.

Flat background < 10^5 dru demonstrated

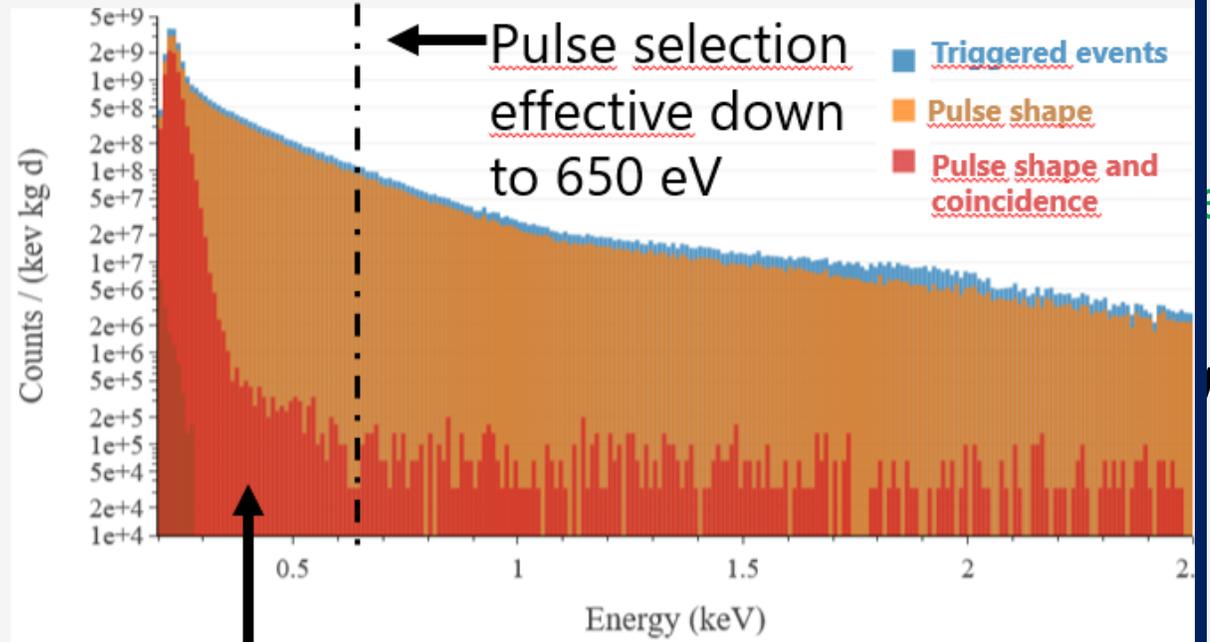
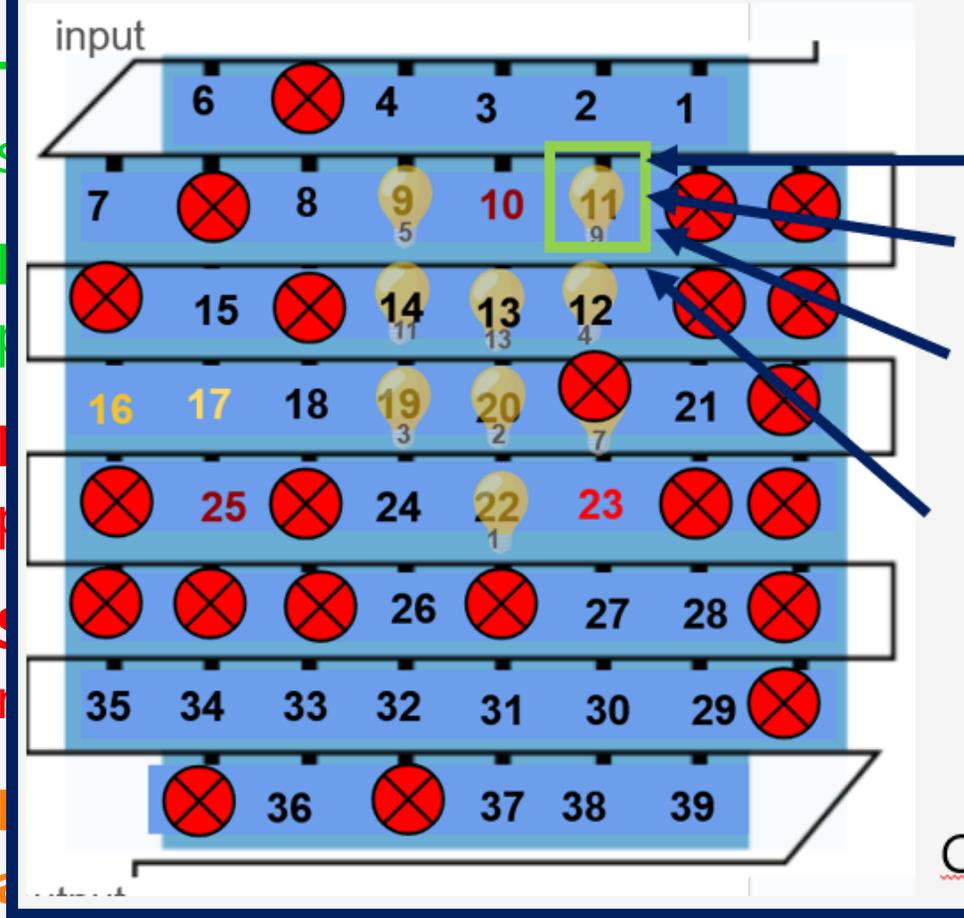
- Above ground
- Passive internal and external Pb shields

To probe background < 650 eV

- Lower threshold
- More active pixels
- **Overall better samples are needed**

STACK-01 RESULTS FROM 01/25

(Many!) missing pixels **do not allow**
vetoing from some directions



Counts **not** compatible with noise false positives

needed

factor

ted

elds

Conclusions last meeting: produce more uniform arrays

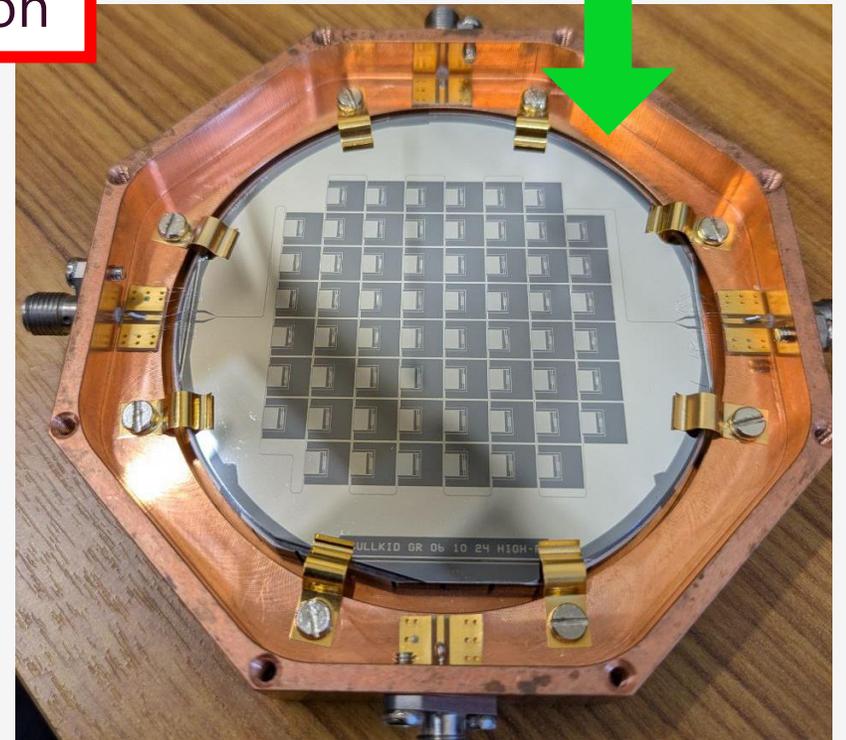
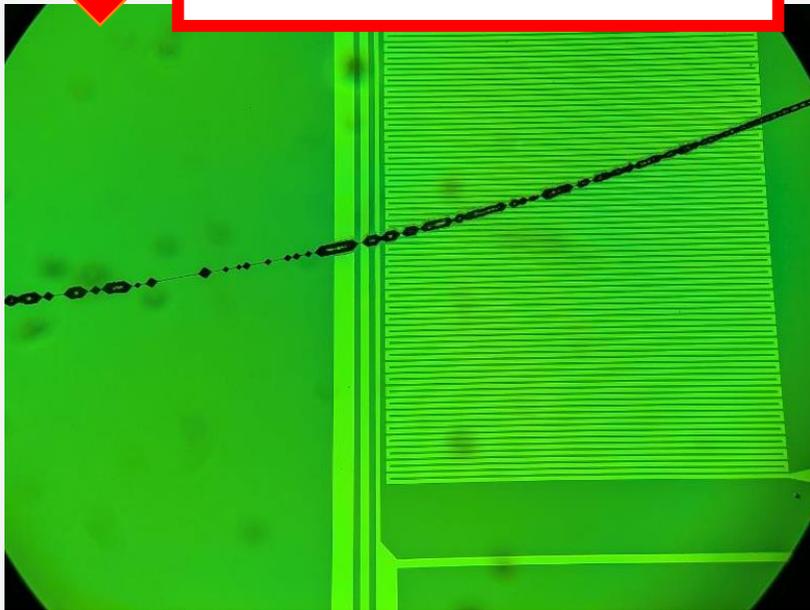
Fabrication in **Grenoble** 10/02 – 21/02

- **3 wafers delivered from Ferrara**

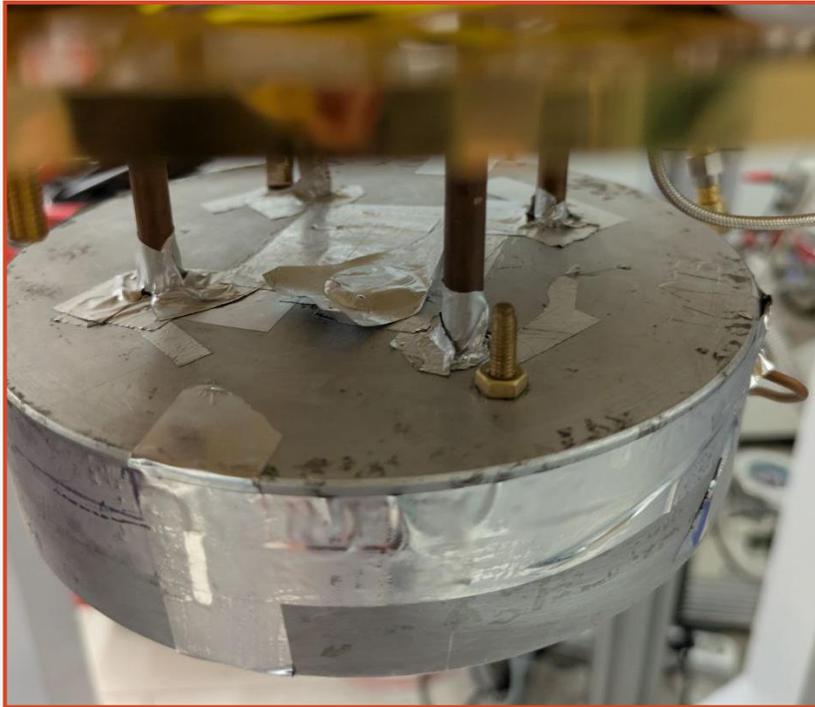
#3 lithography successful

#1 Scratched surface

#2 Cracked silicon



Fabrication status of additional stack elements: STACK-04



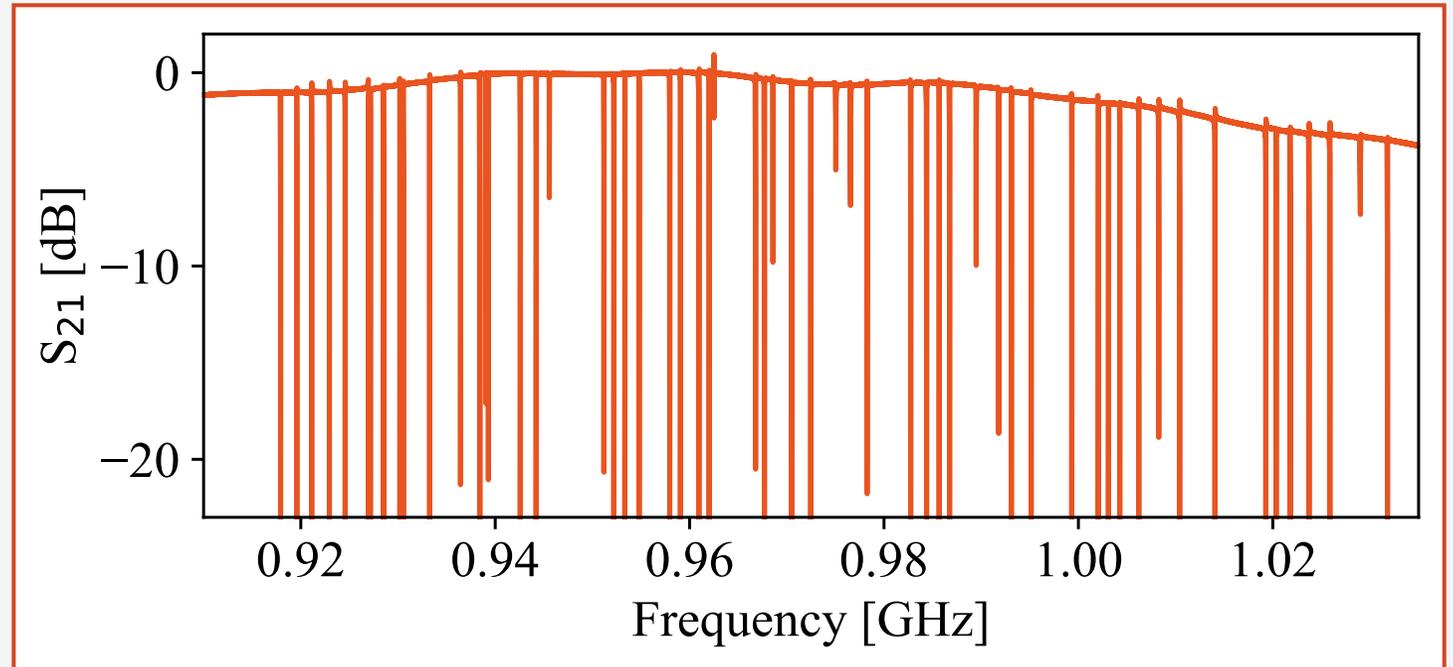
Stack-04: 60nm Al

57 working pixels out of 60

Quality factor (median): 120k

Coupling Q factor (median): 130k

Bonding across the line removed artifacts



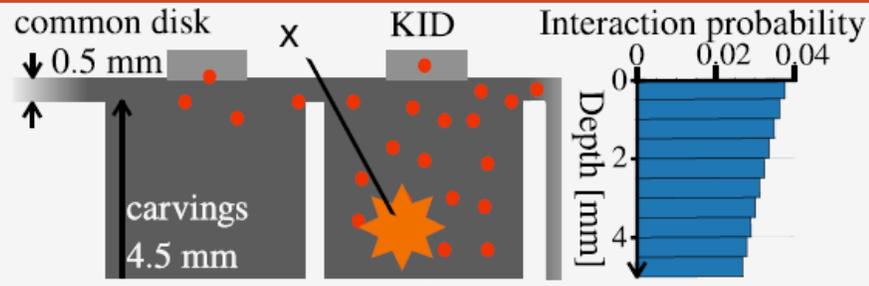
Preliminary test in **ROME** + bondings

P165 @ 30mK; Q_i > 5M

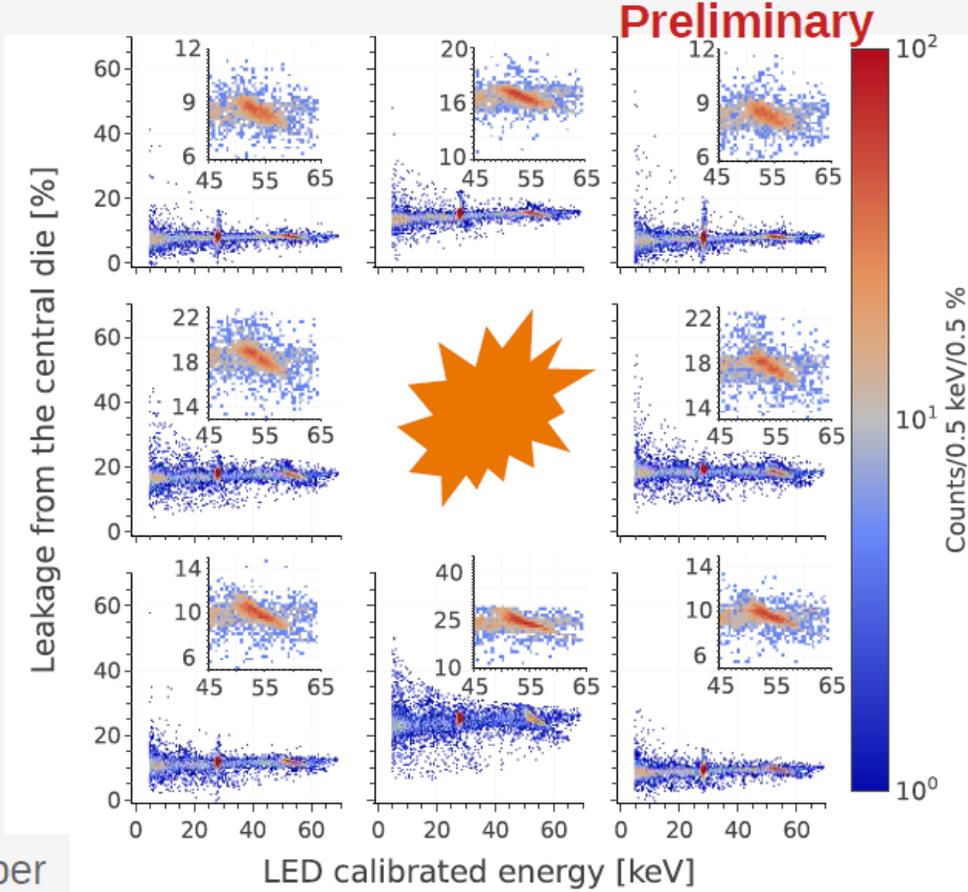
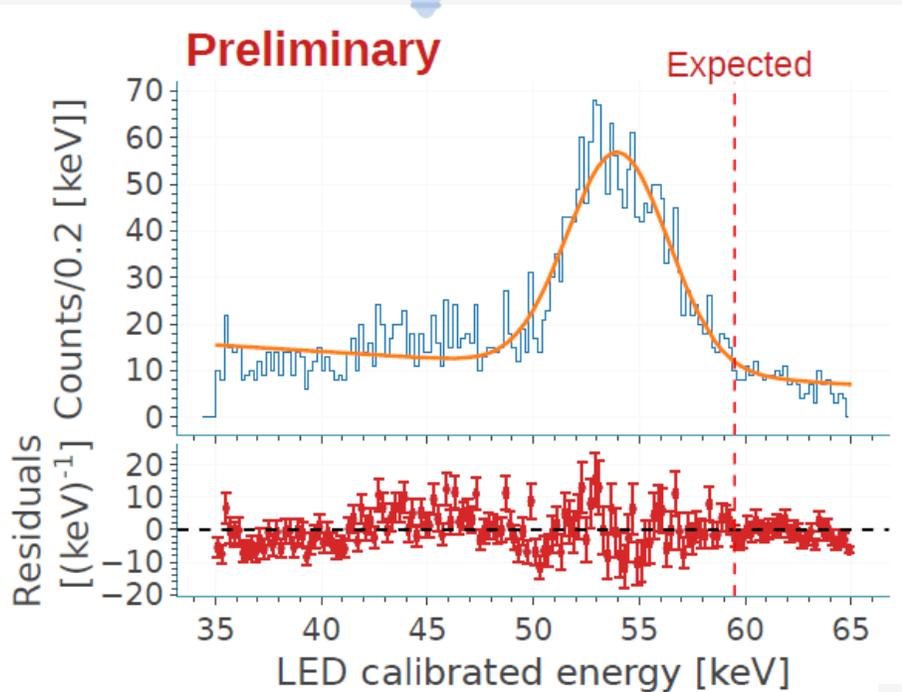
Single wafer configuration

Bulk (Am) vs Surface (LED) events

See talk by M. Folcarelli



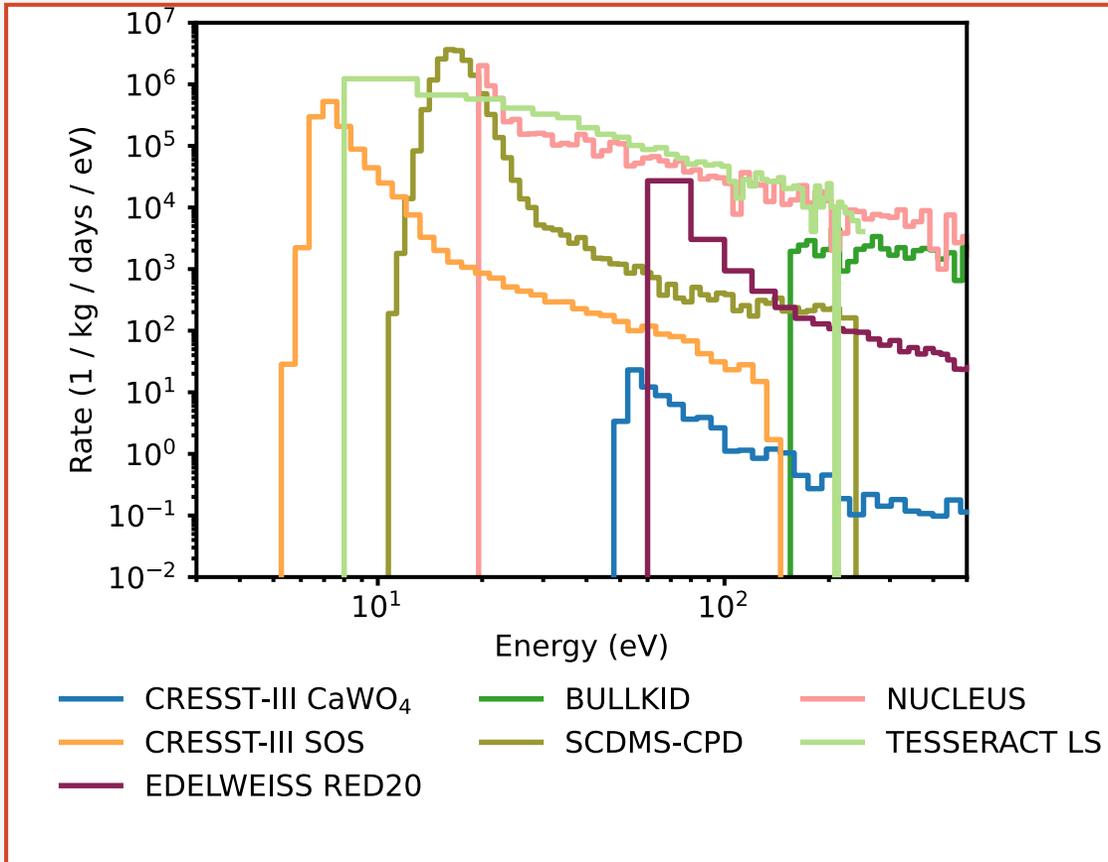
- Dedicated cooldown with Am source (59.5 keV X-Ray)
- -10% discrepancy between calibrations
- Same leakage between bulk and LED



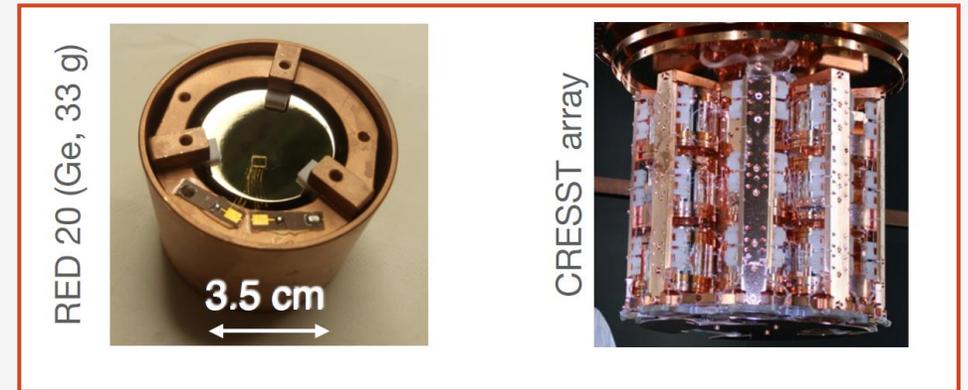
Upcoming Paper

Background issue in low-T experiments

Not understood excess background rising at low energies



- Phonon bursts (crystal-support friction) ?
- Lattice relaxations after cool down?
- Phonon leakage from interactions in the supports?



Excess workshop 2025
Santa Fe, 31 May
<https://indico.cern.ch/event/1502420/>

This background limits the sensitivity of present experiments

Background with mild shield

15 KIDs in 2 Clusters

Run time: **19 Apr 22:00 -> 5 May 8:00**

Live hours per cluster: 290

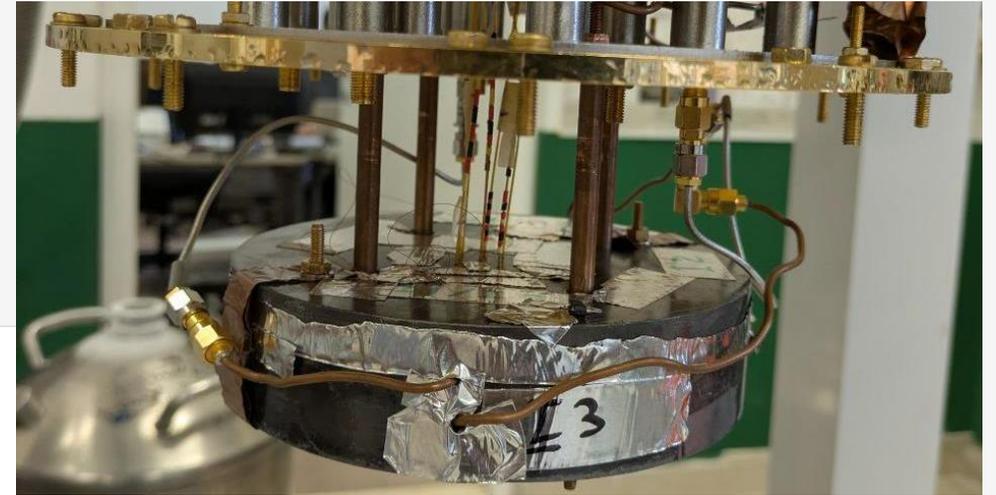
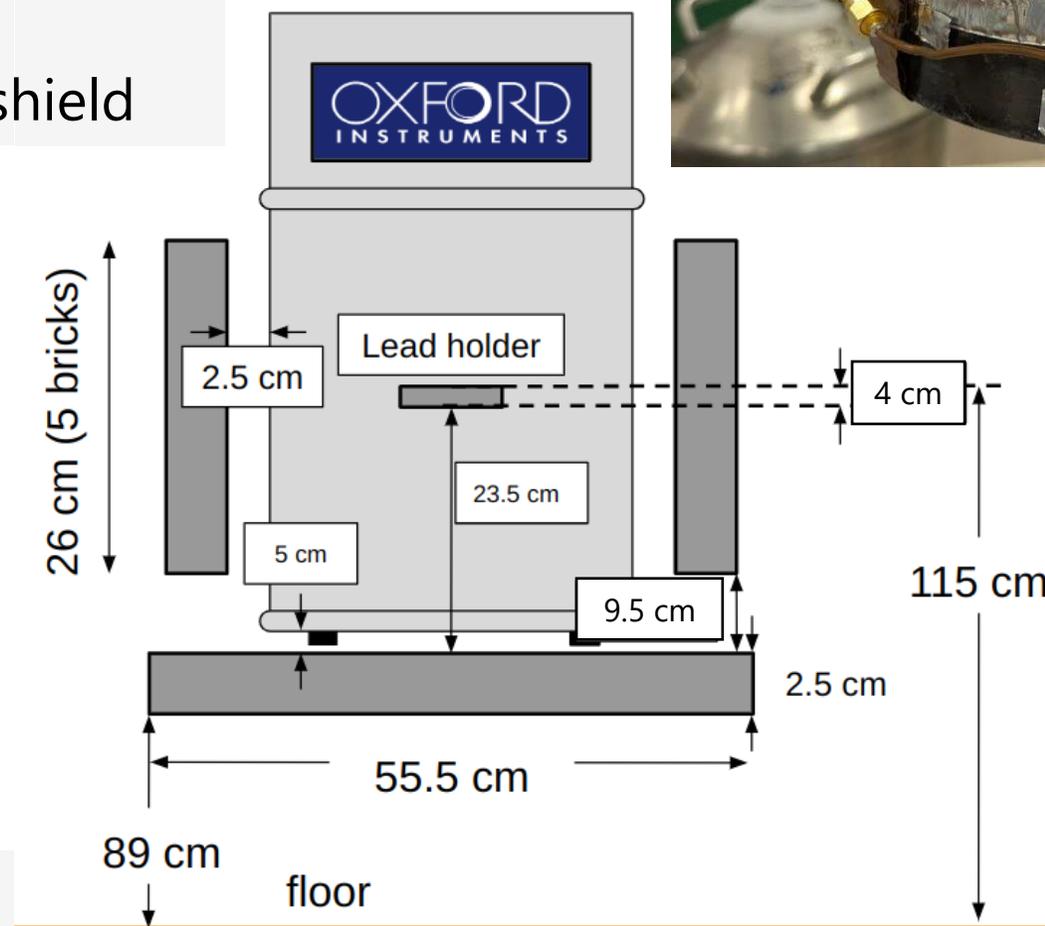
Internal and external lead shield

		1	2	3	4	5	
13	12	11	10	8	7	9	6
14	15		16	17	18		19
27	26	25	24	23	22	21	20
29	28	30	31	32	33	34	35
43	42	41	40	39	38	36	37
44	45	46	47	48	49	50	51
	57	56	55	54	53	52	

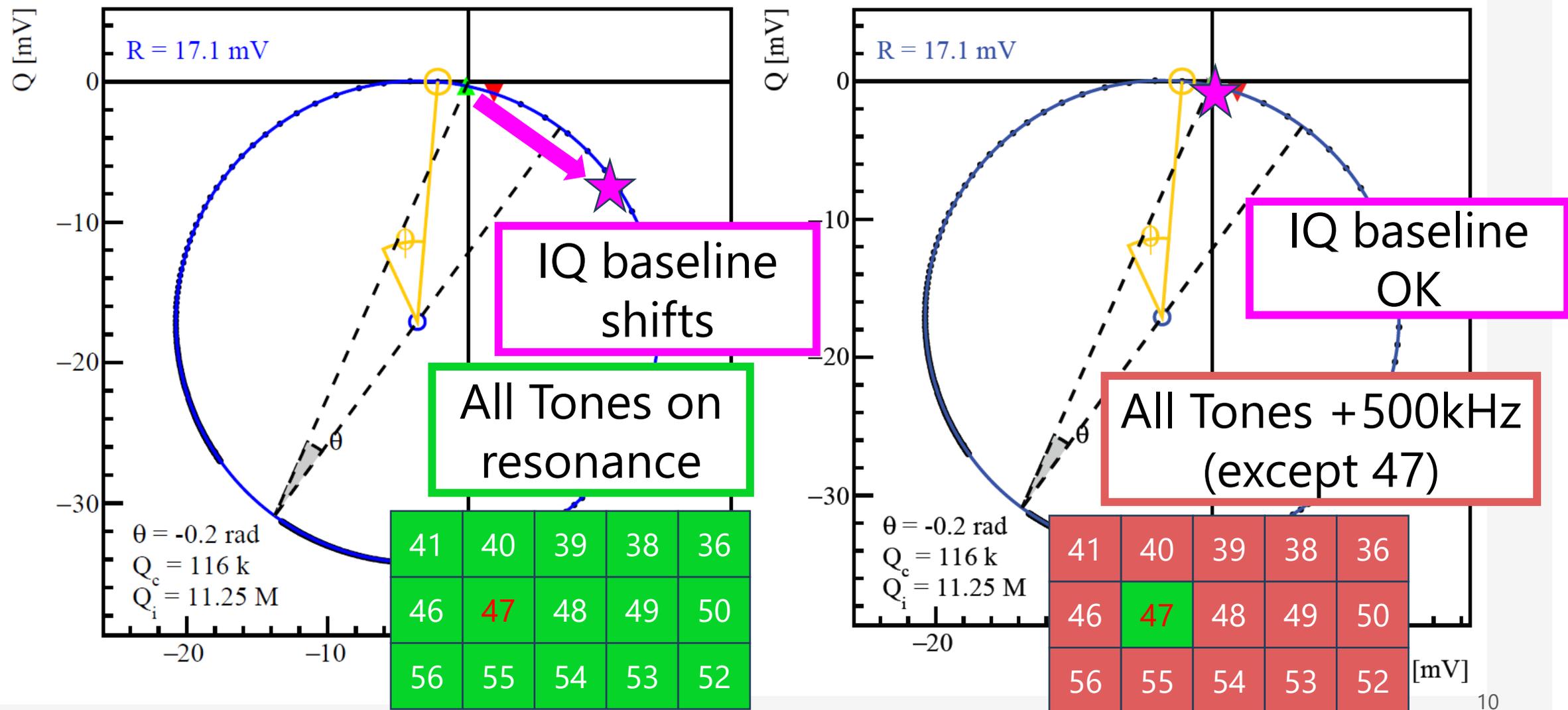
Indexes: Frequency ordering

Triggering

Acquired in coincidence as veto

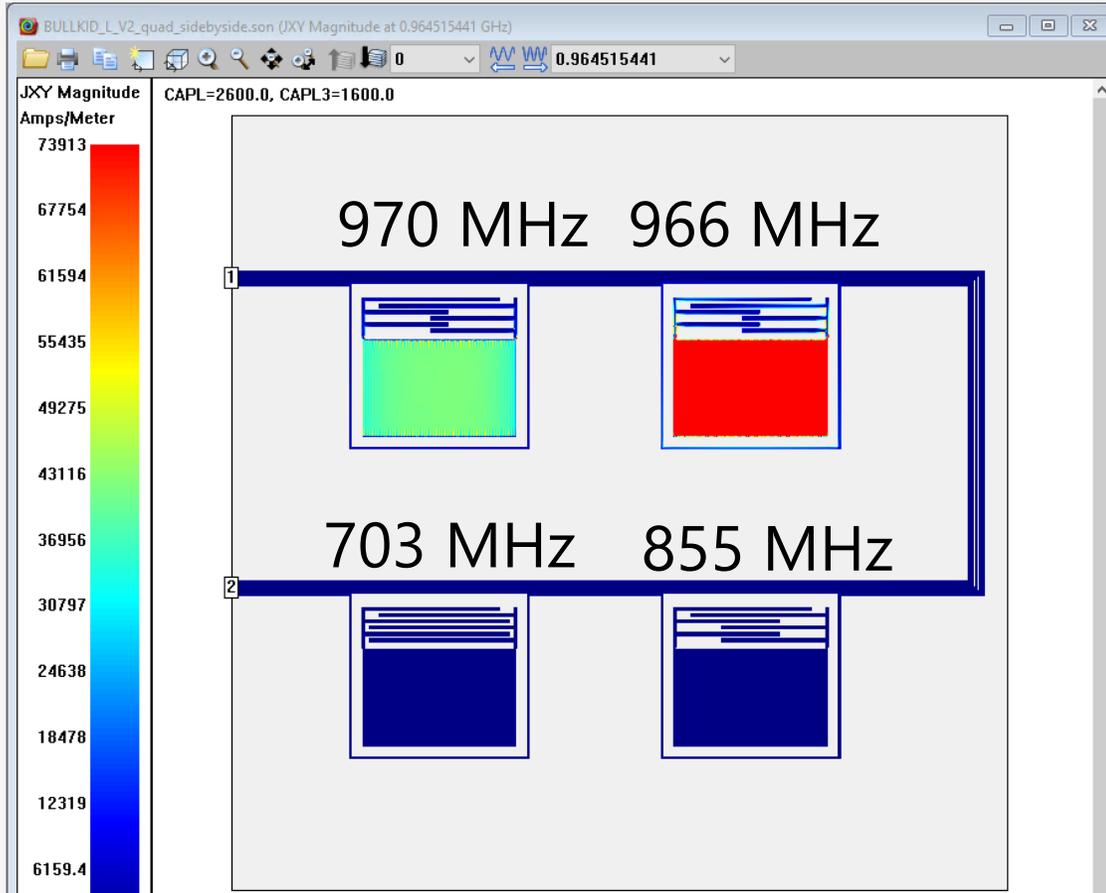


More pixels, more electronic x-talk

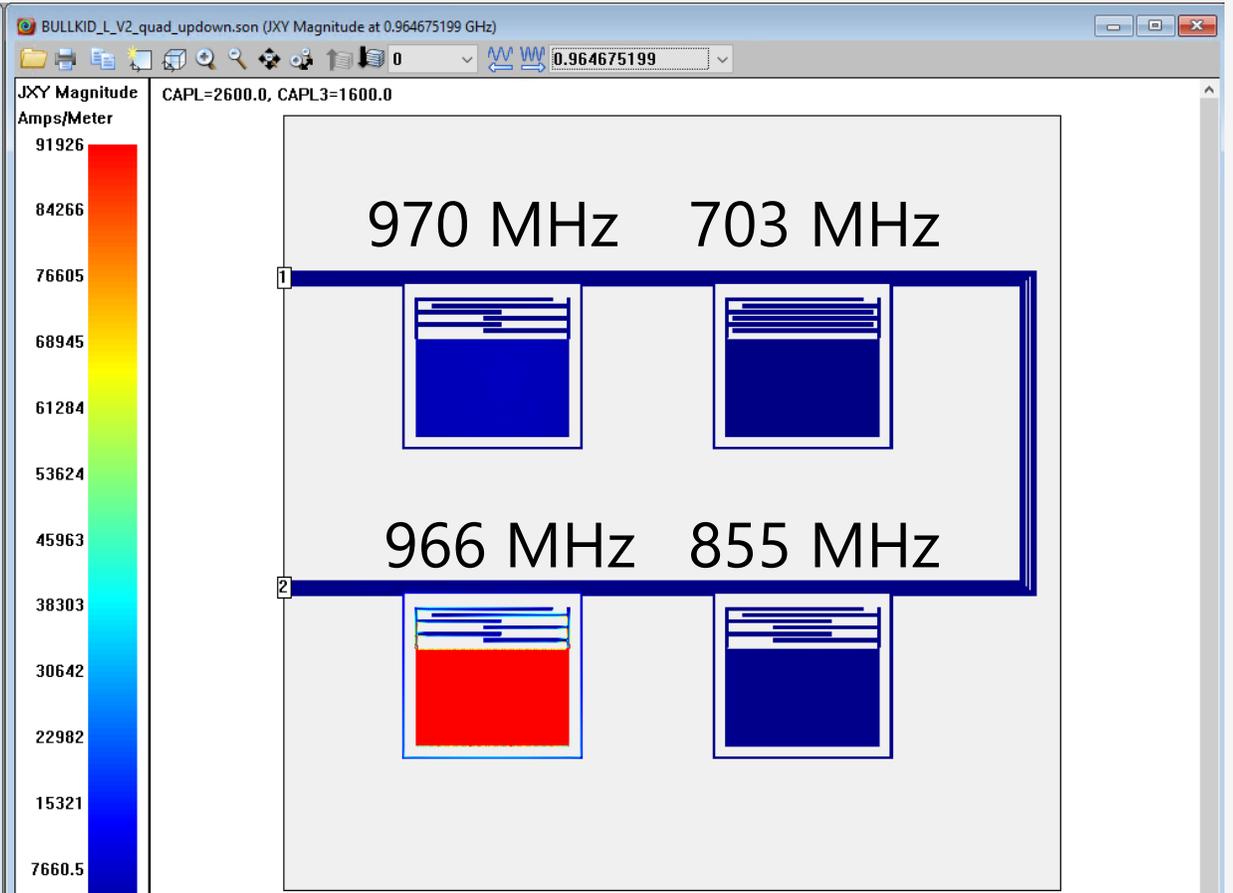


Sonnet simulations of x-talk induced by proximity

See talk by M. Cappelli

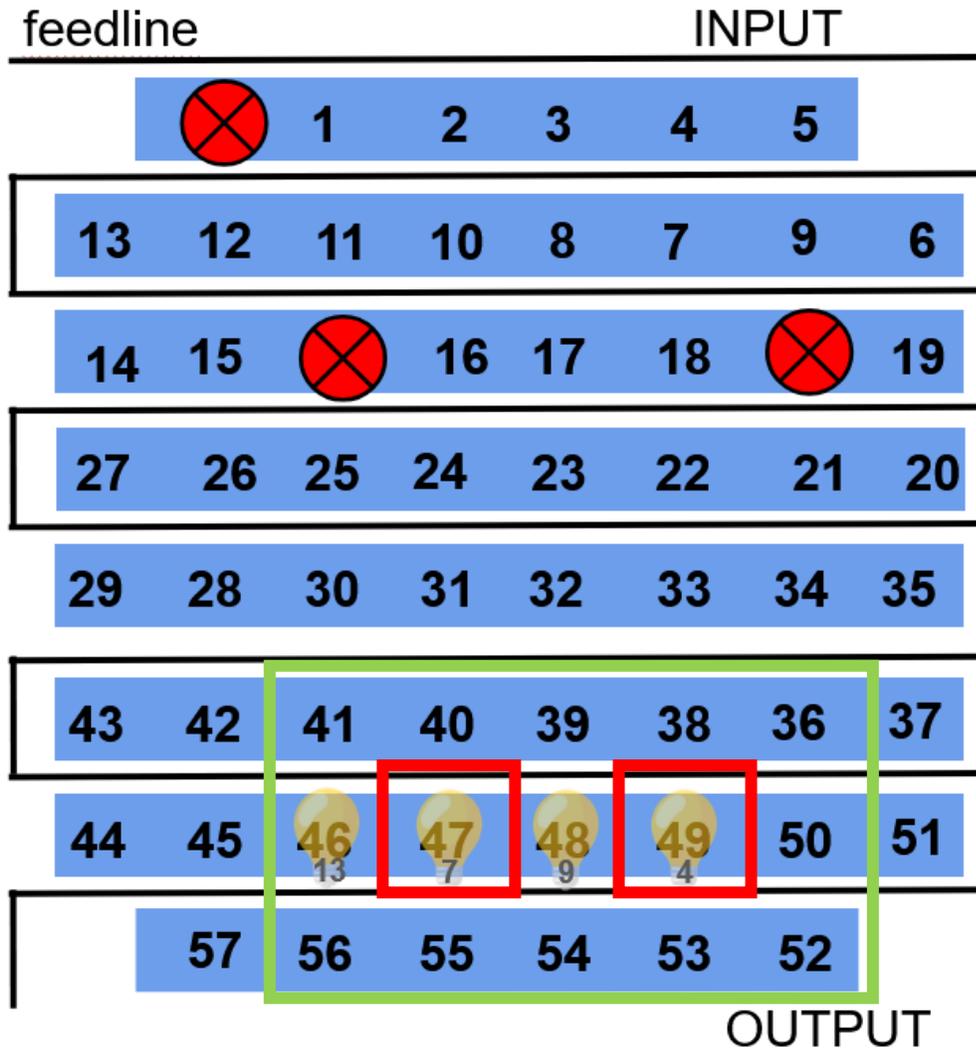


Induced current density: 30%



Induced current density: 3%

More pixels, more possible clusters



- F7 --> KID-47 R 10.6 mrad / keV; σ_0 **35 eV**
- F4 --> KID-49 R 9.3 mrad / keV; σ_0 **30 eV**
- F9 --> KID-48 Distrupted by microwave x-talk

Power distribution:

47 and 49 @ opt power / asym 0.19

38, 40, 46, 50, 53, 55 @ -12 dBm TxPwr

36, 49, 41, 48, 52, 54, 56 @ -16 TxPwr

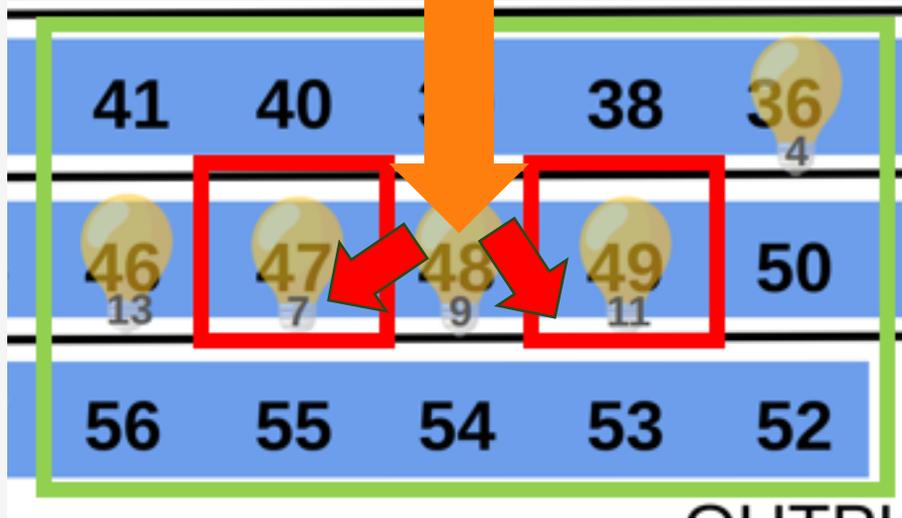
Power limited by amplifier -1dB

compression and by KID EM X-talk

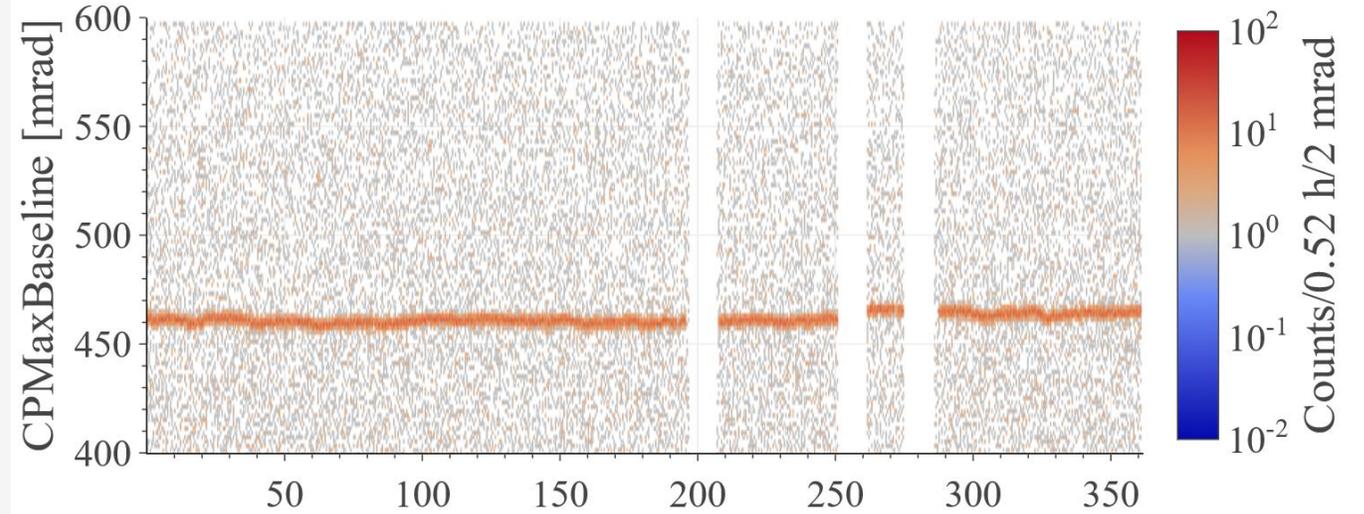
41	40	39	38	36
46	47	48	49	50
56	55	54	53	52

Stability evaluation

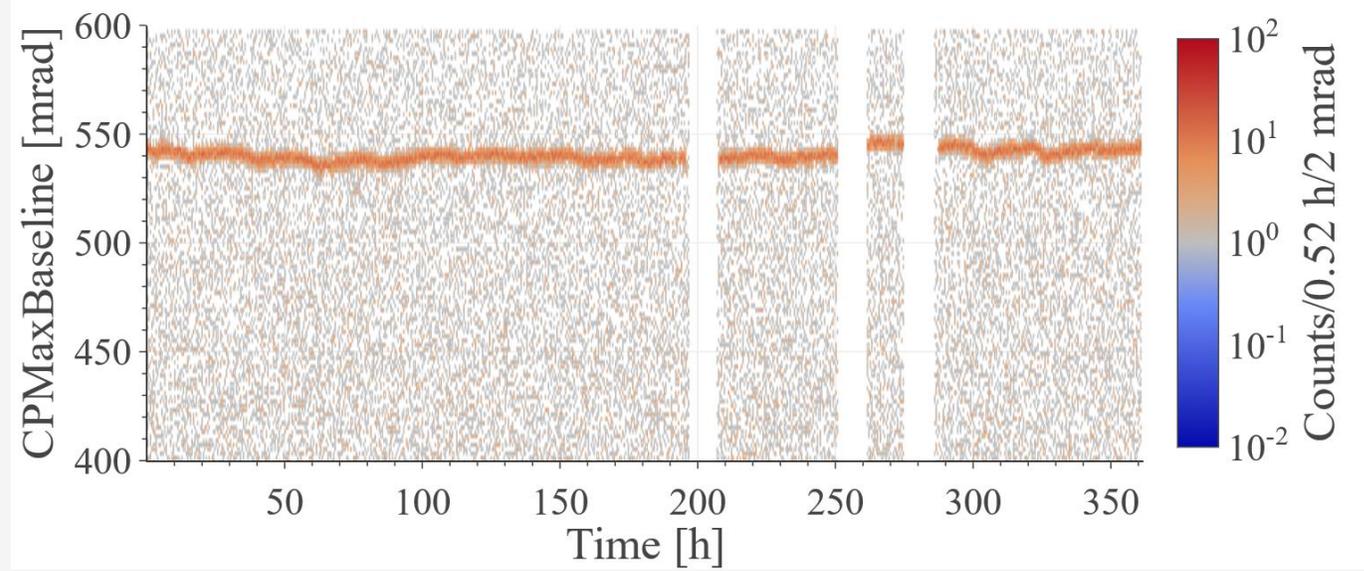
Fire LED on KID-48,
evaluate stability of
masters with leakage
signal



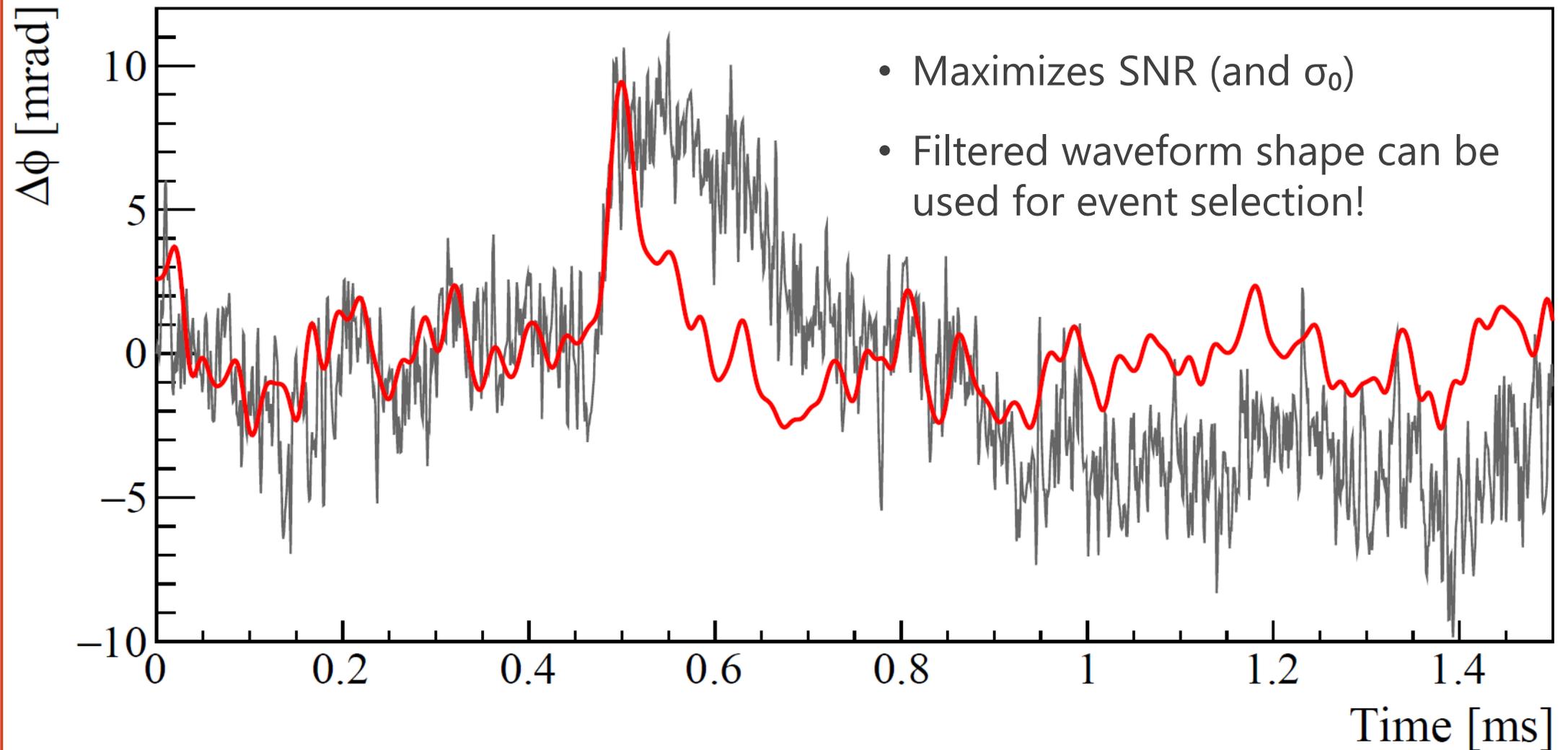
Control LED stability KID-49



Control LED stability KID-47

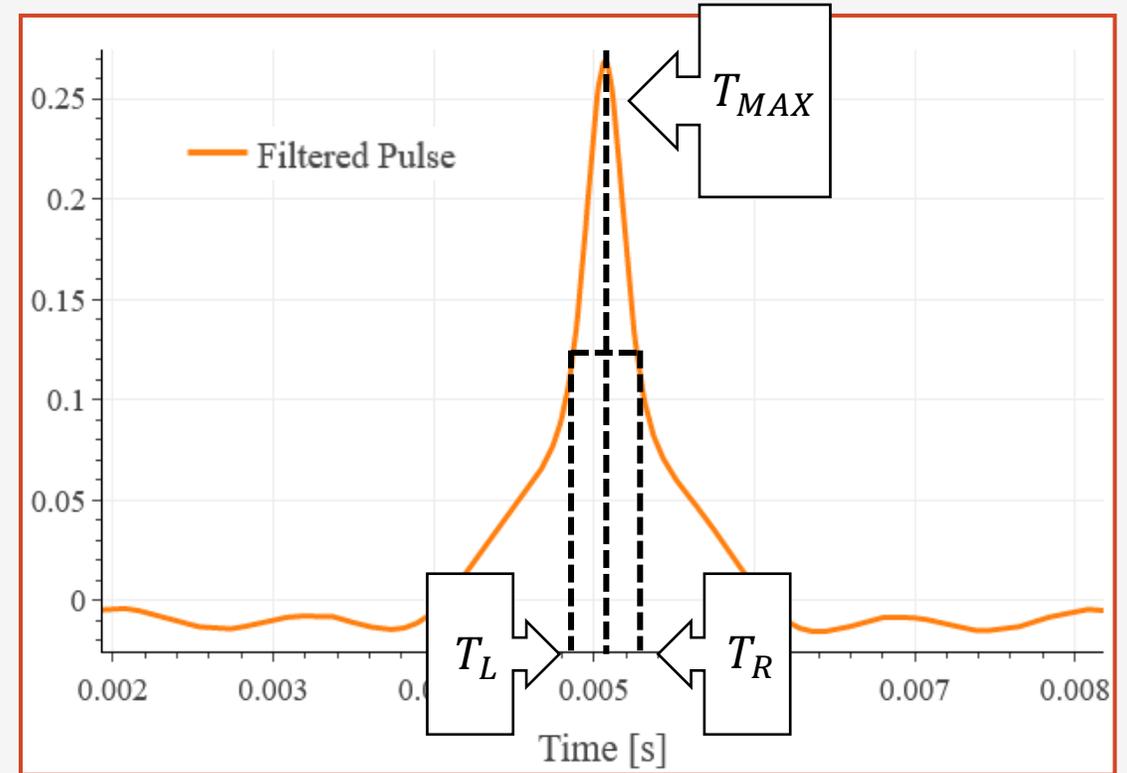
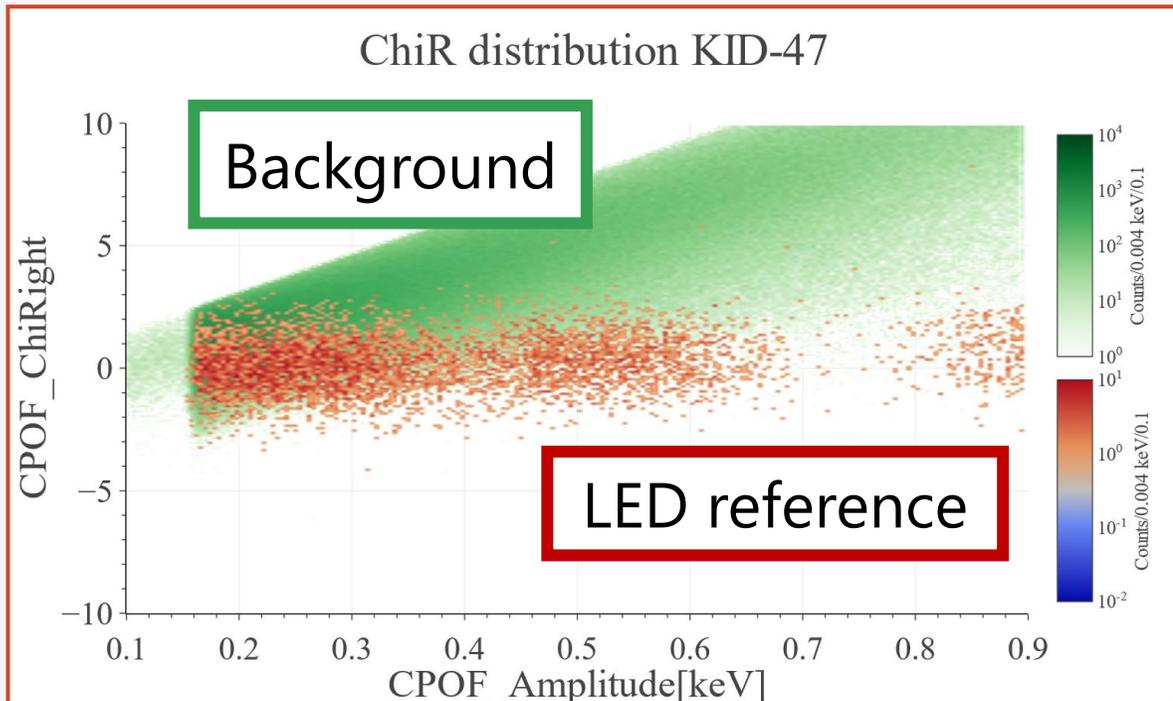


Optimum filter used for energy reconstruction



Pulse selection, shape cuts on OF parameters

- Cut **Chi2** (index of deviation from template in the whole window)
- Cut on **ChiLeft** (index of deviation at T_L)
- Cut on **ChiRight** (index of deviation at T_R)

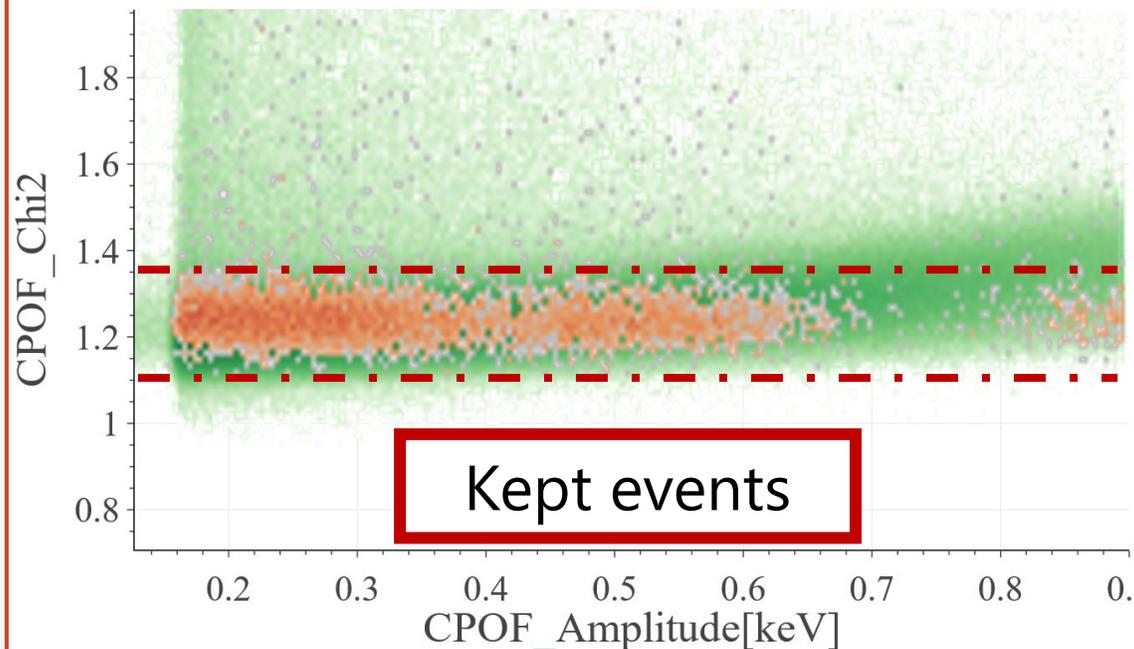


$$\chi^2(t_i) = \frac{[A(t_i) - \alpha_i A(t_{max})]^2}{\sigma^2 (1 + \alpha_i^2) - 2\alpha_i R(t_i - t_{max})}$$

Pulse selection, shape cuts

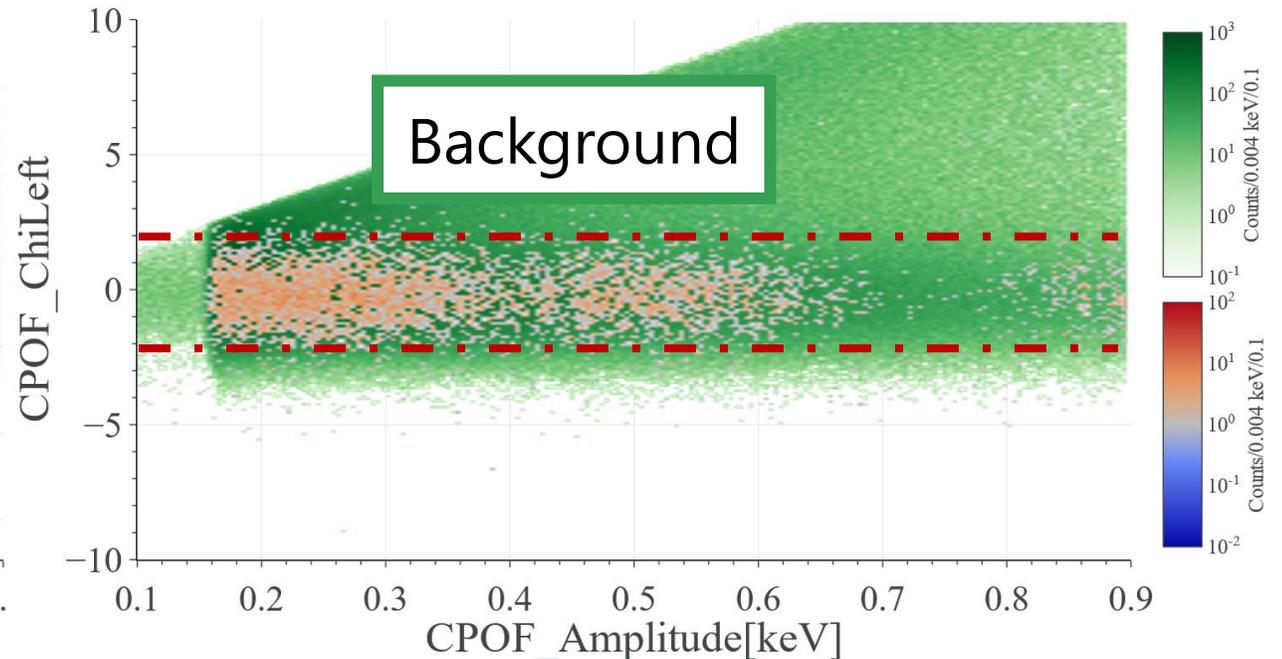
$$\chi^2(t_i) = \frac{[A(t_i) - \alpha_i A(t_{\max})]^2}{\sigma^2 (1 + \alpha_i^2) - 2\alpha_i R(t_i - t_{\max})}$$

Chi2 distribution KID-47



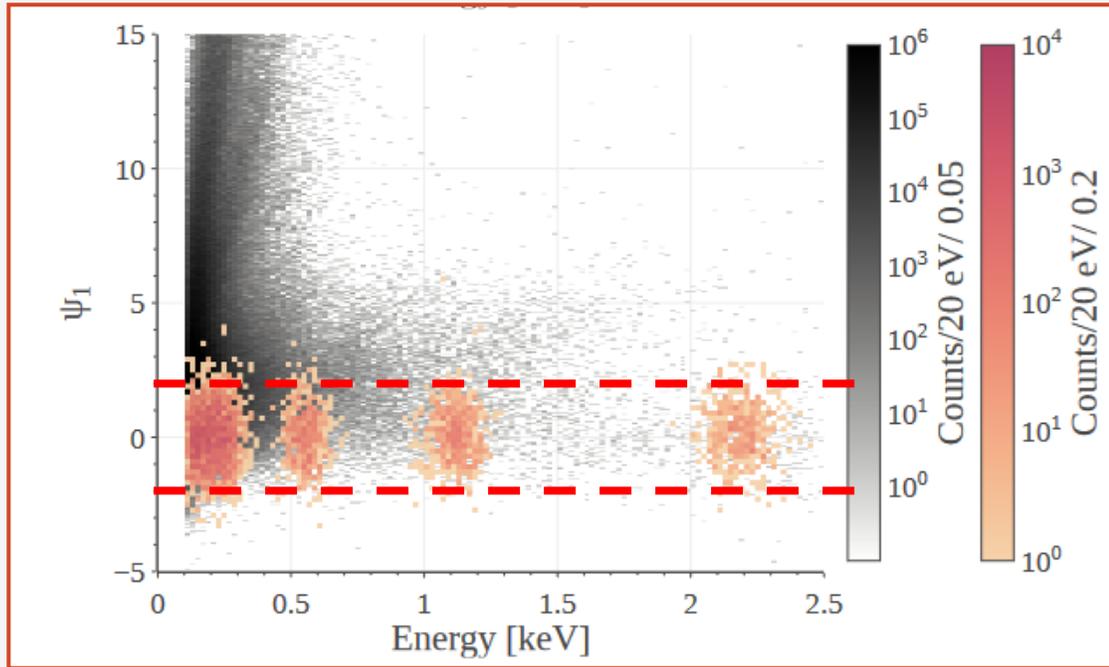
Chi2 $\in [1.1, 1.38]$

ChiL distribution KID-47

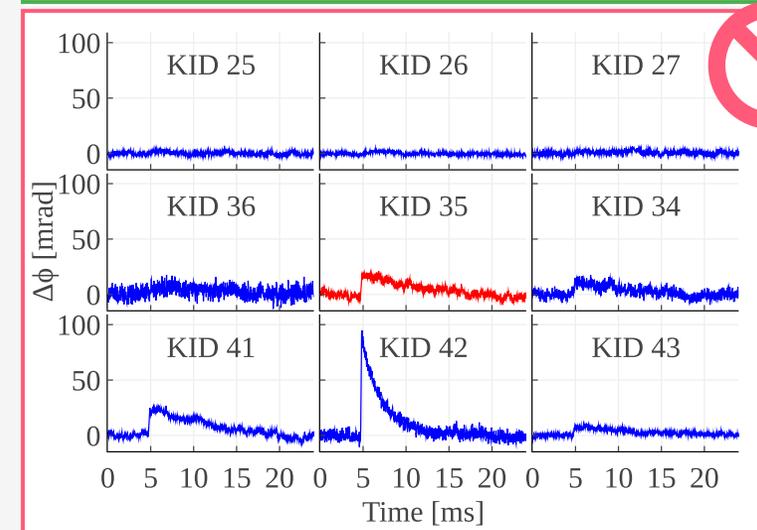
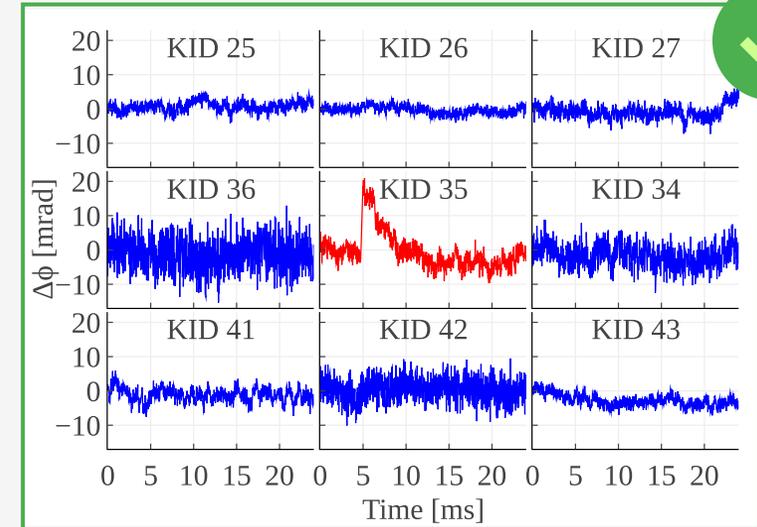


ChiL $\in [-2, 2]$

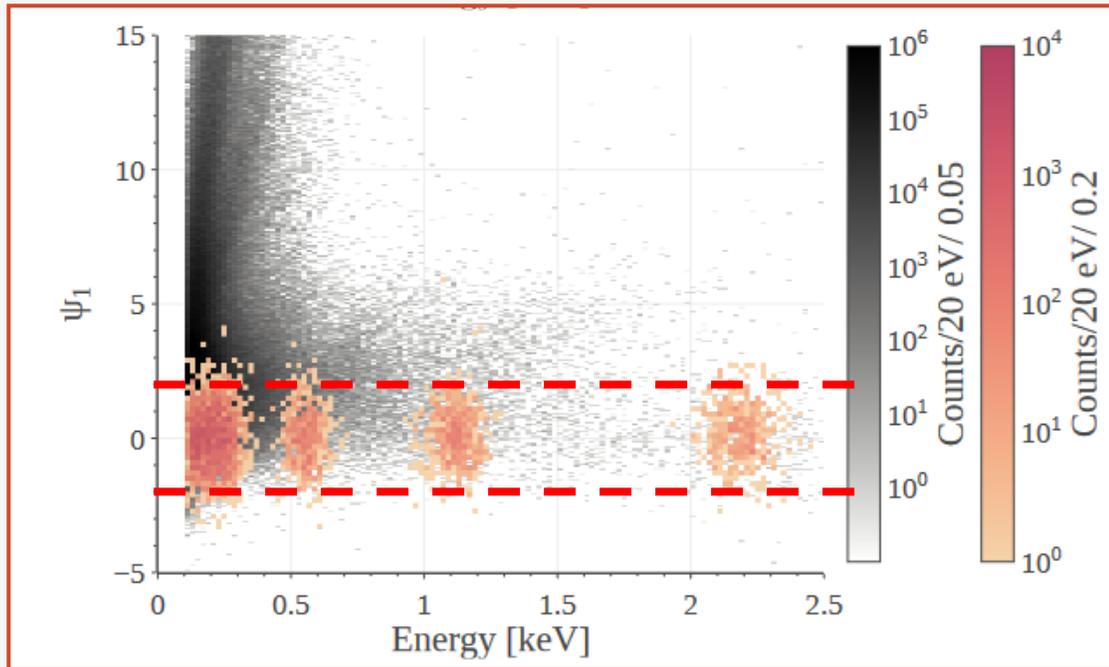
Evaluation of cluster cuts



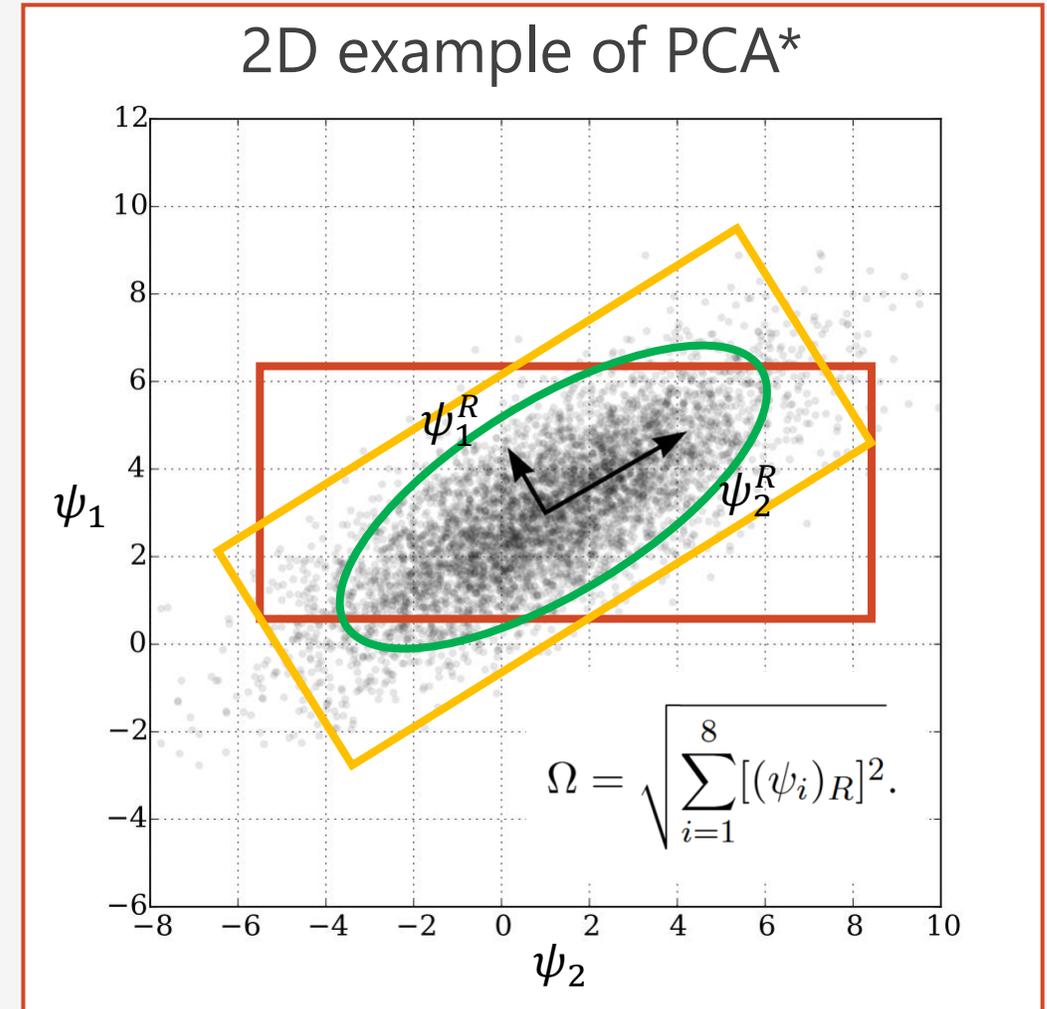
$$\psi_i = \frac{\delta\phi_i - (\delta\phi_c \cdot \mu_{r_i})}{\sqrt{\sigma_{0,i}^2 + (\sigma_{0,c} \cdot \mu_{r_i})^2}}$$



Evaluation of cluster cuts

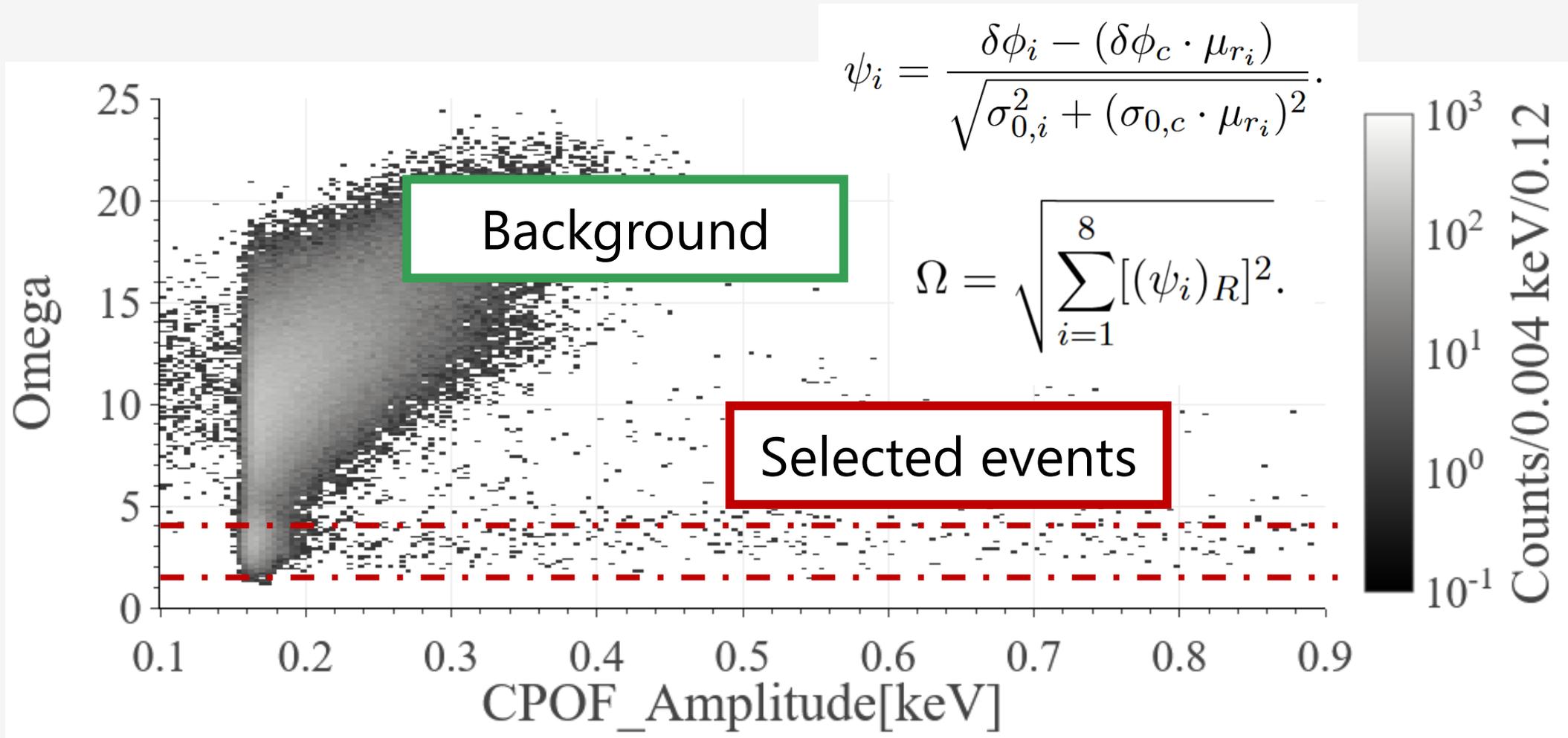


$$\psi_i = \frac{\delta\phi_i - (\delta\phi_c \cdot \mu_{r_i})}{\sqrt{\sigma_{0,i}^2 + (\sigma_{0,c} \cdot \mu_{r_i})^2}}$$

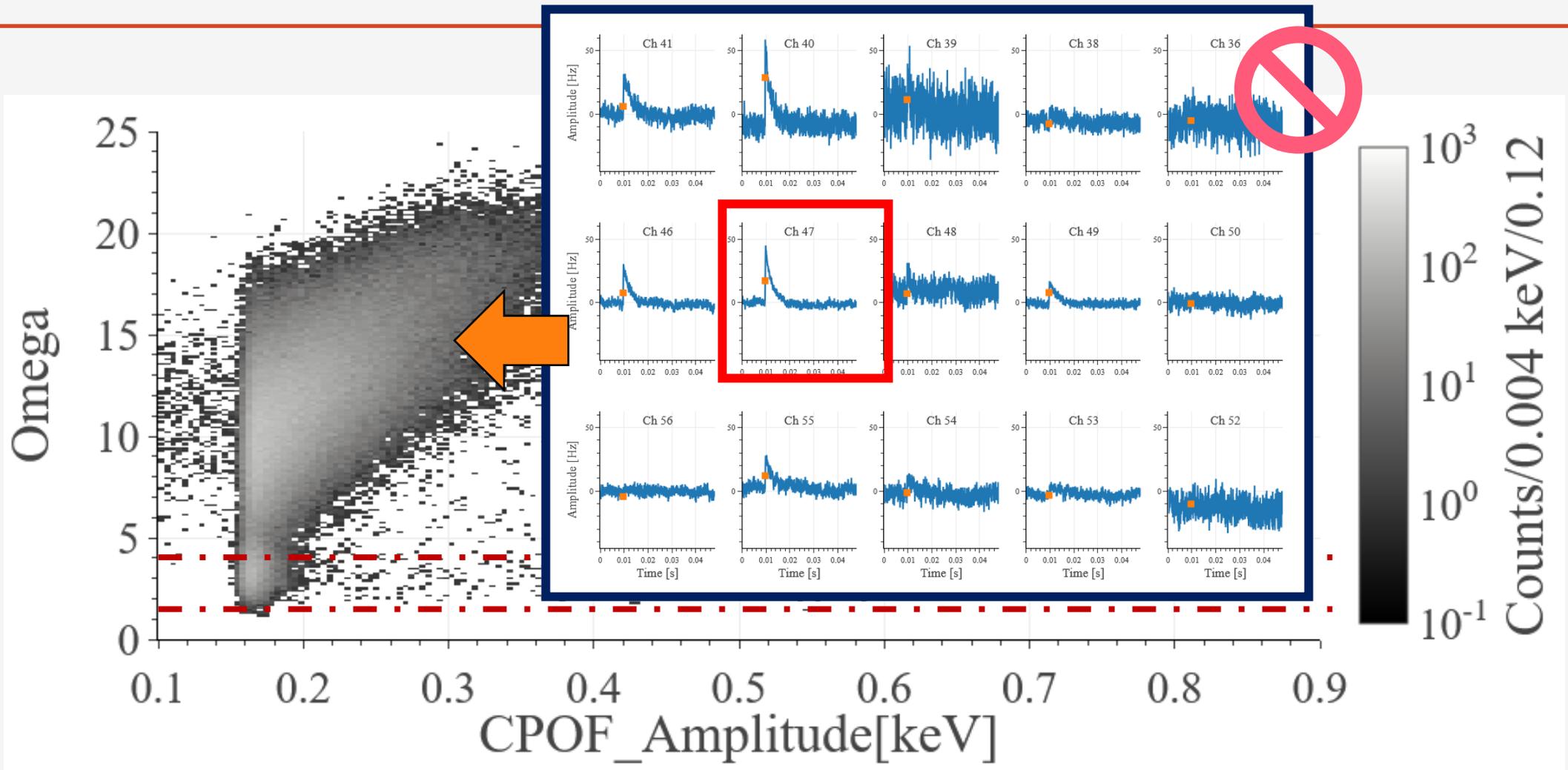


* Not actual data from BULLKID

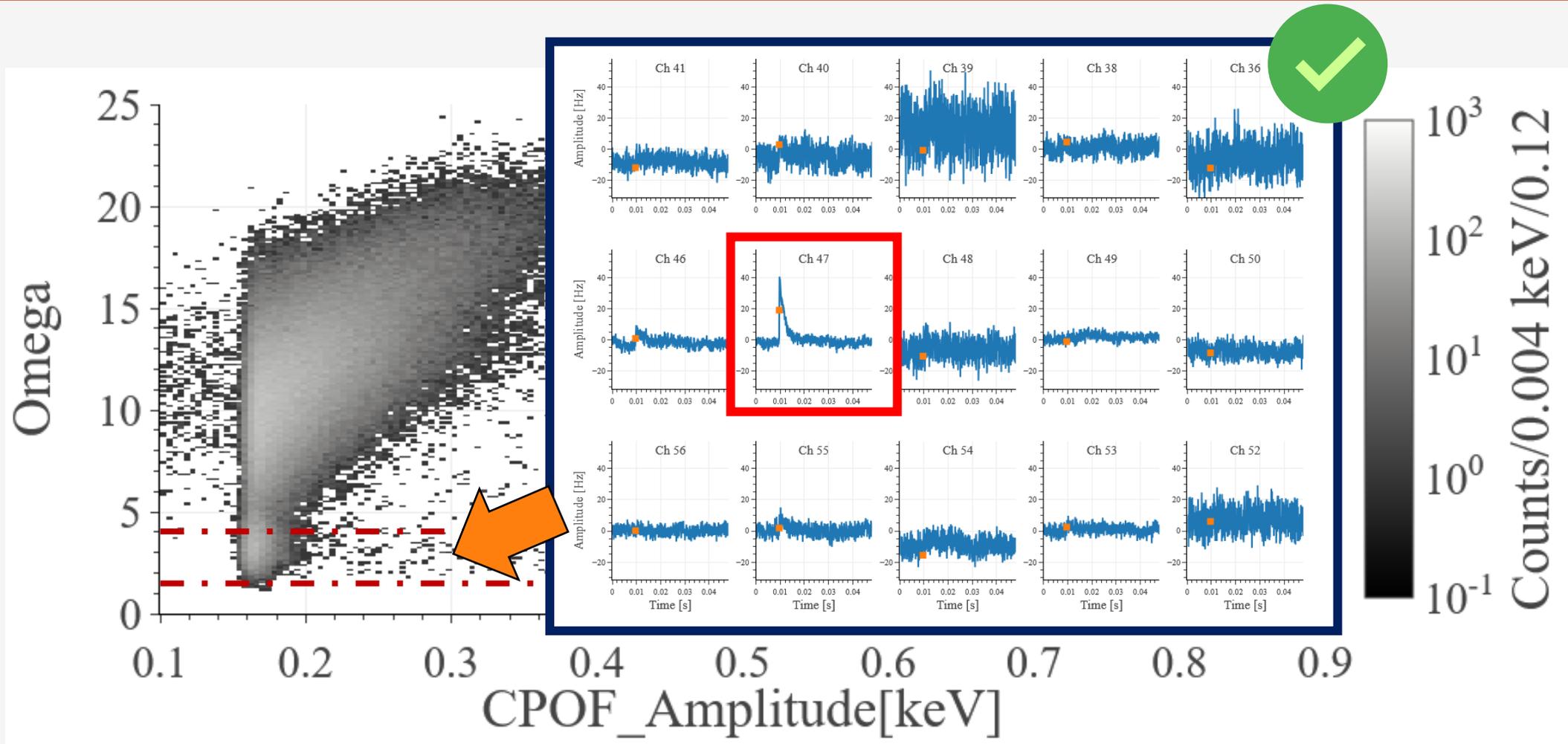
Pulse selection, coincidence cuts (KID-47)



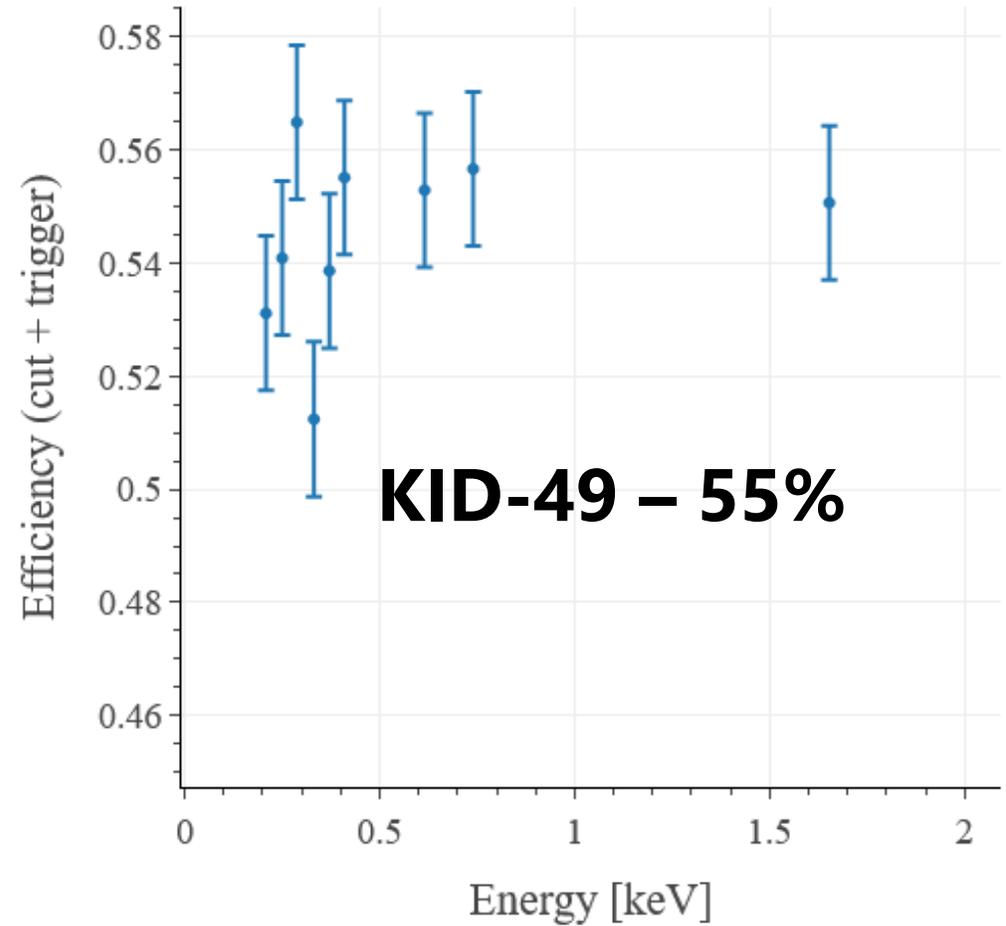
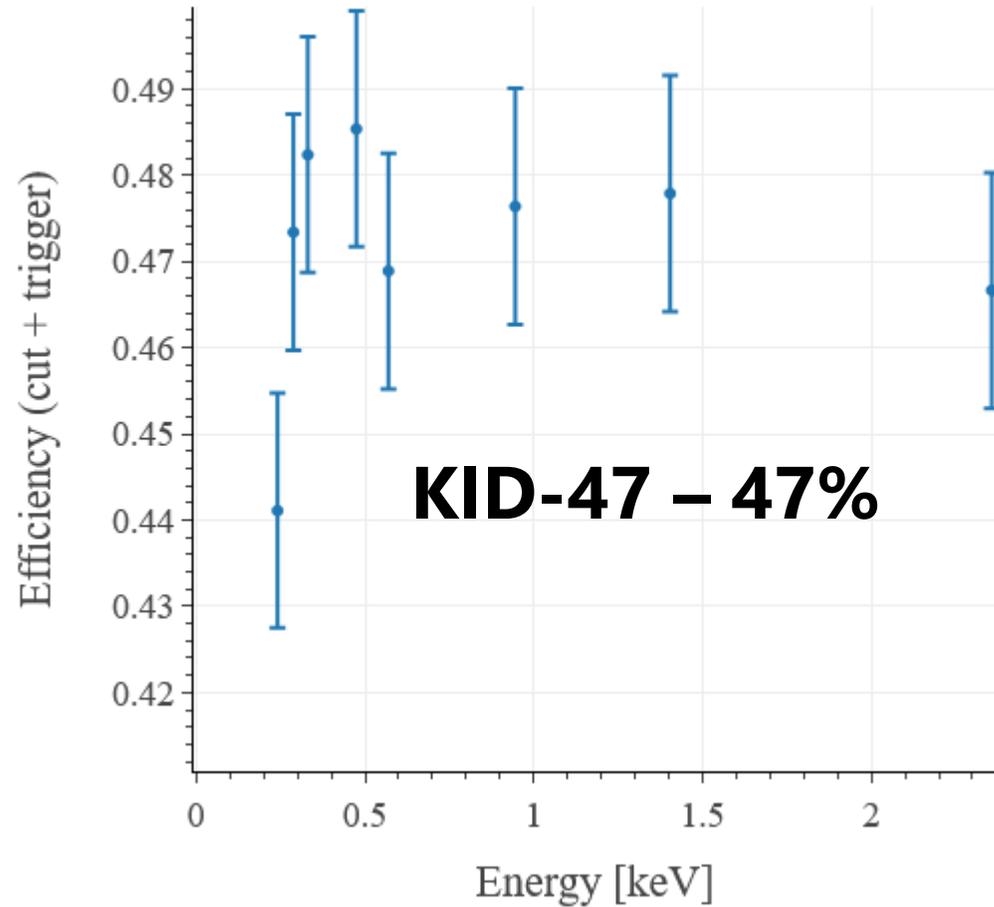
Pulse selection, coincidence cuts (KID-47)



Pulse selection, coincidence cuts (KID-47)

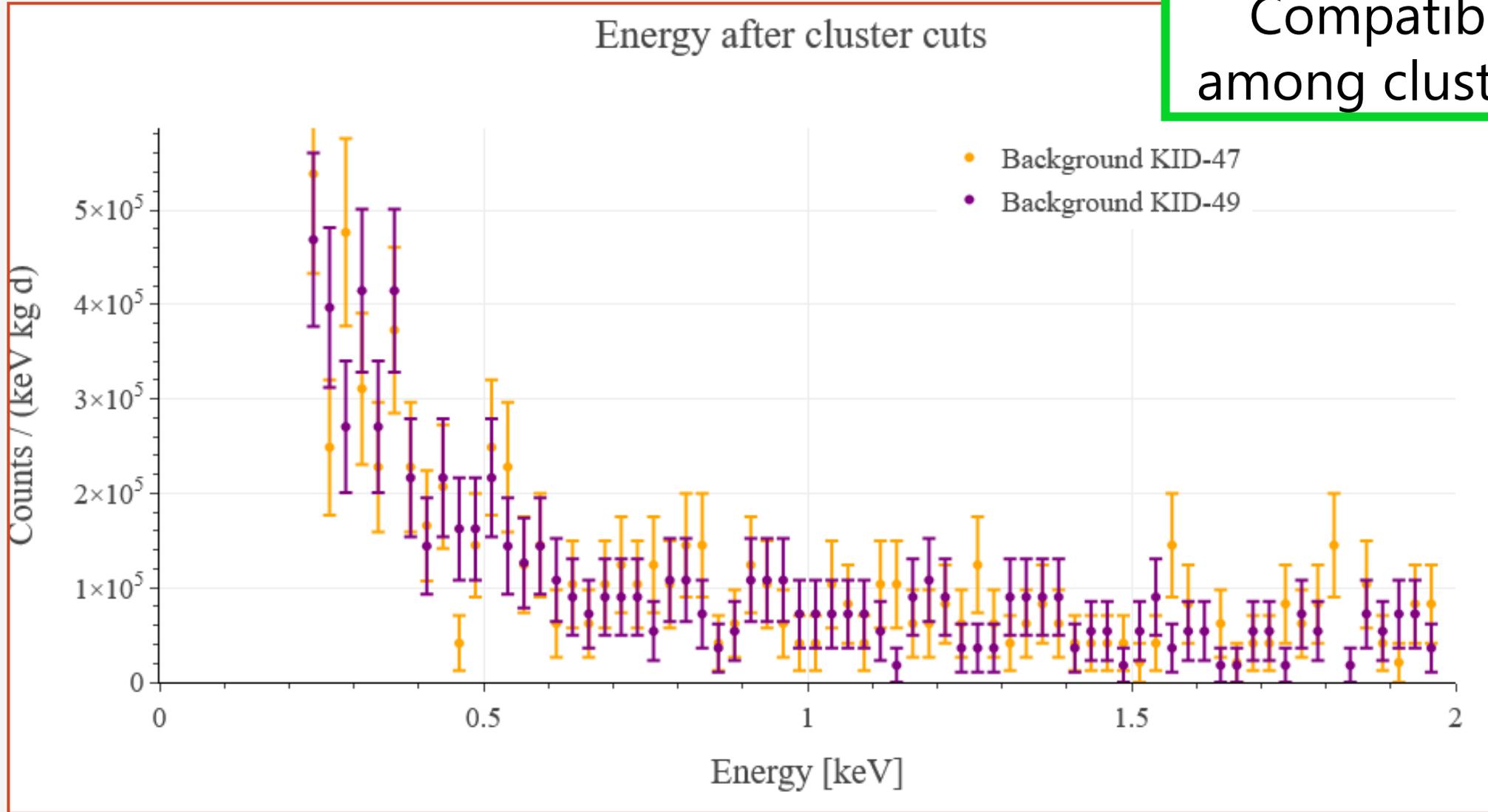


Efficiency evaluation on LED events

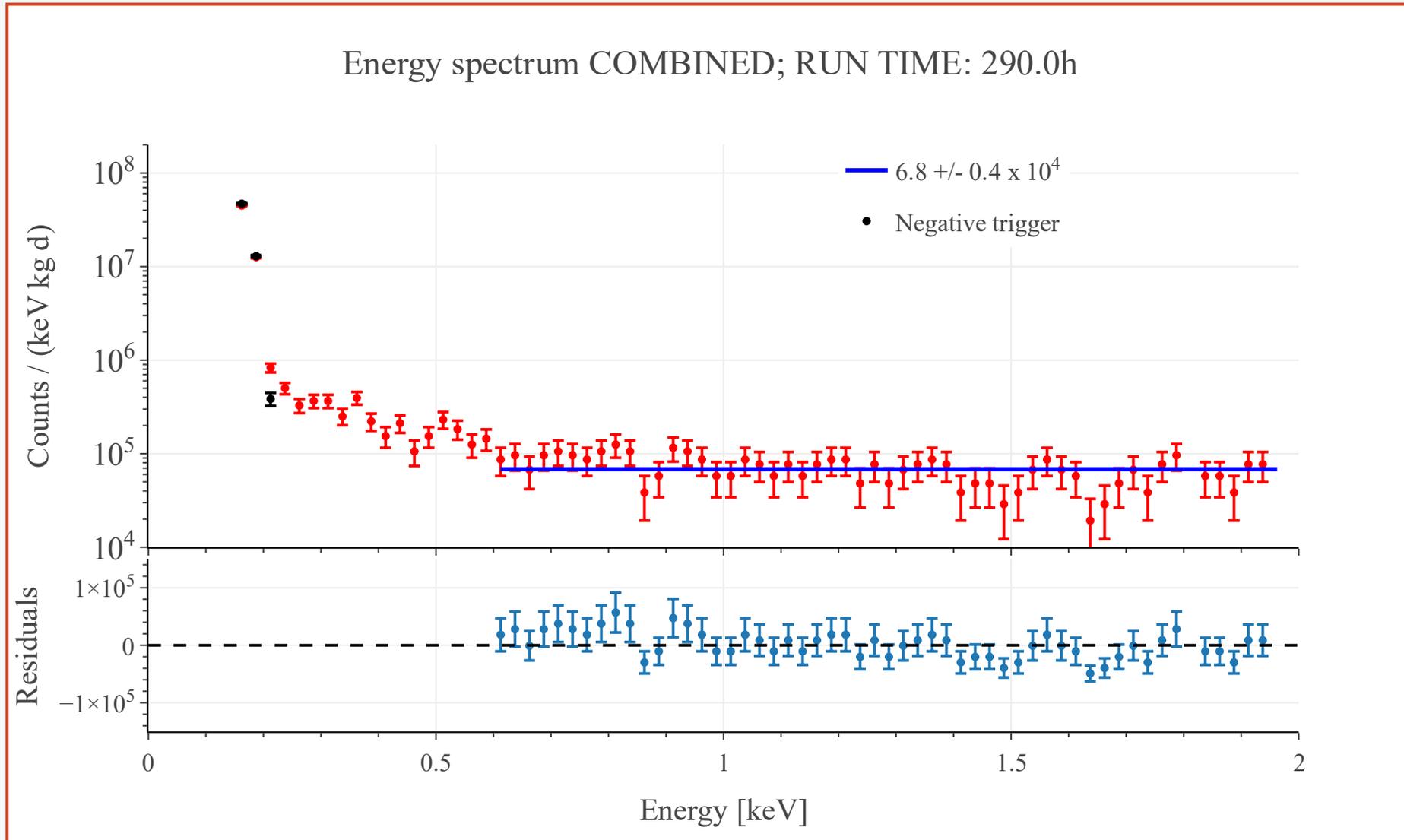


Background: result on surface @Sapienza U., Pb shield, 290 live hours

Compatible among clusters!



Background: result on surface @Sapienza U., Pb shield, 290 live hours



Background: result on surface @Sapienza U., Pb shield, 290 live hours

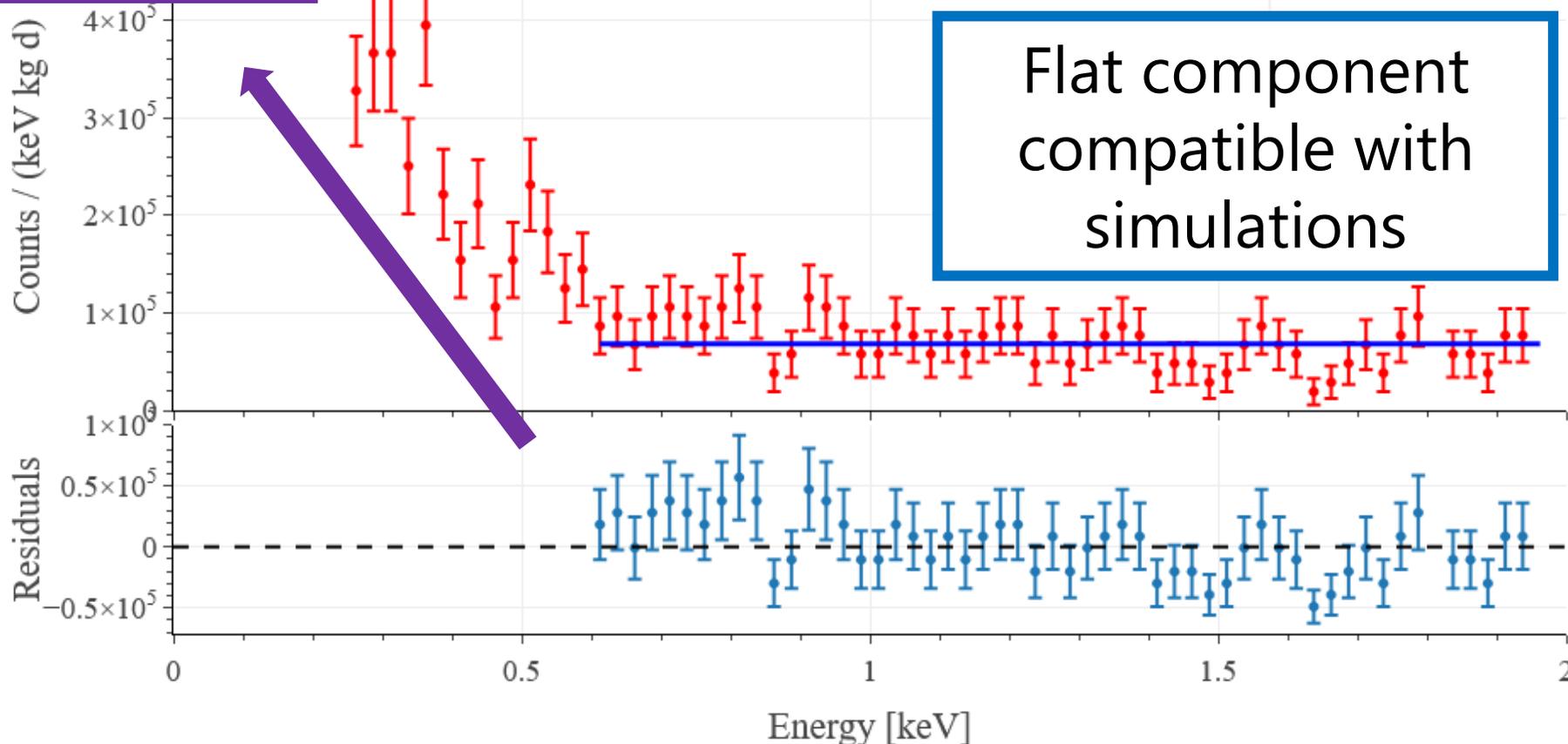
Increase by a factor ≈ 5
Particle origin ?

Energy spectrum COMBINED; RUN TIME: 290.0h

Preliminary

— $6.8 \pm 0.4 \times 10^4$

Flat component
compatible with
simulations



Background: result on surface @Sapienza U., Pb shield, 290 live hours

Energy spectrum COMBINED; RUN TIME: 290.0h

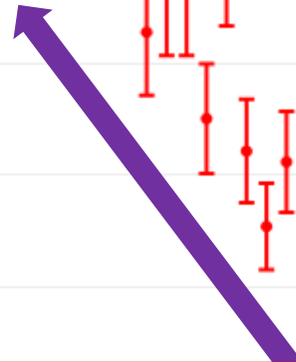
Preliminary

Increase by a factor ≈ 5
Particle origin ?



Counts / (keV kg d)

4×10^5
 3×10^5
 2×10^5
 1×10^5

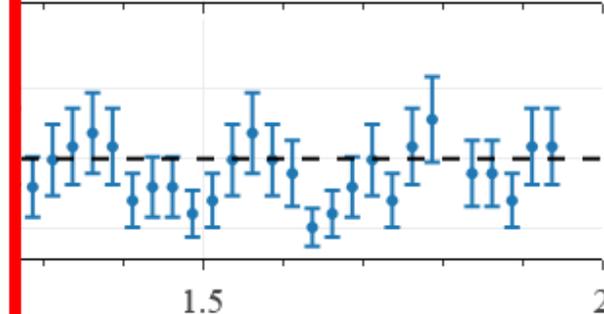


— $6.8 \pm 0.4 \times 10^4$

Flat component
compatible with
simulations

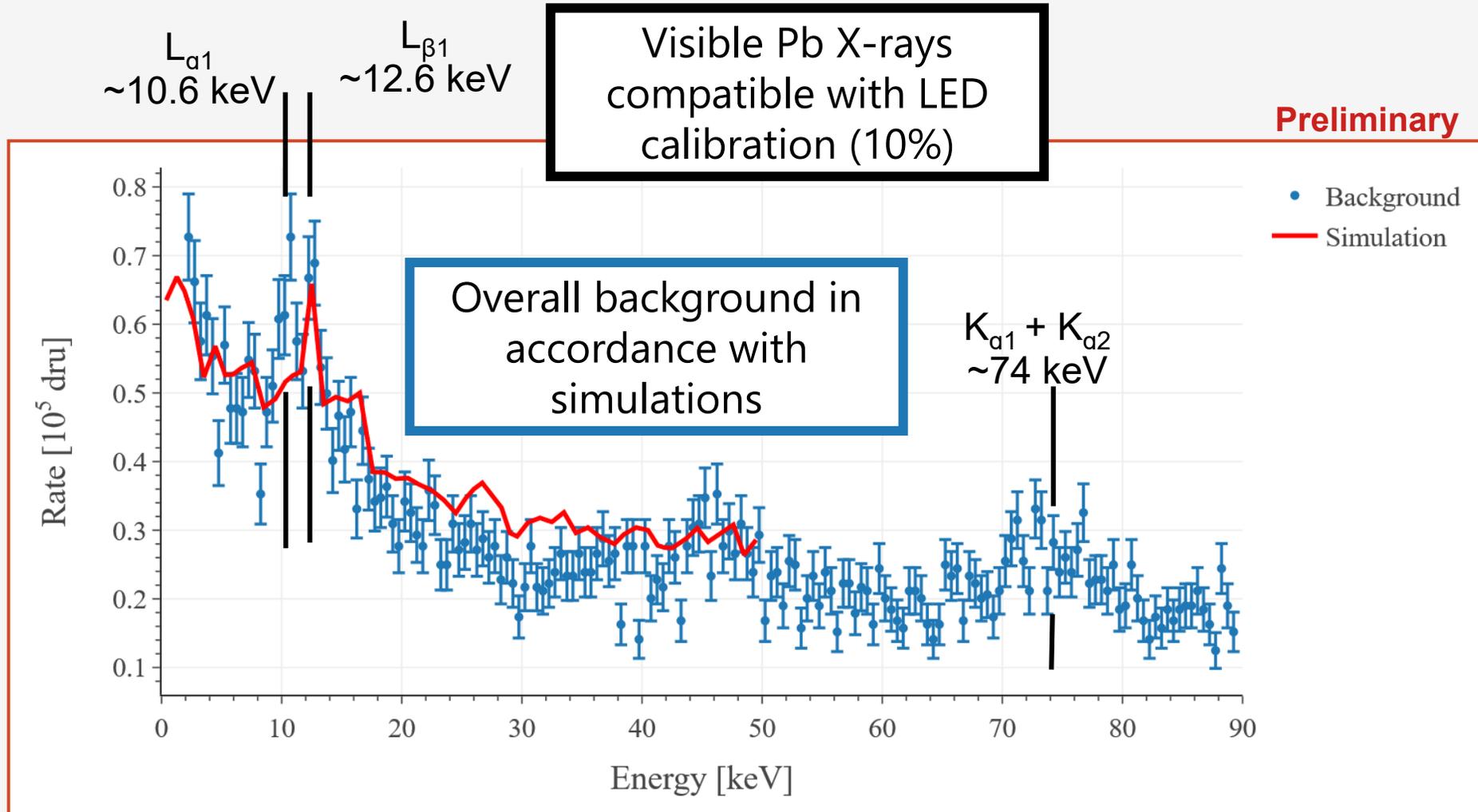
Next steps:

- 1) Move underground and increase shield
- 2) Add fluorescence models in simulations



Energy [keV]

High Energy Spectrum and Simulation Comparison



Conclusion and future prospects

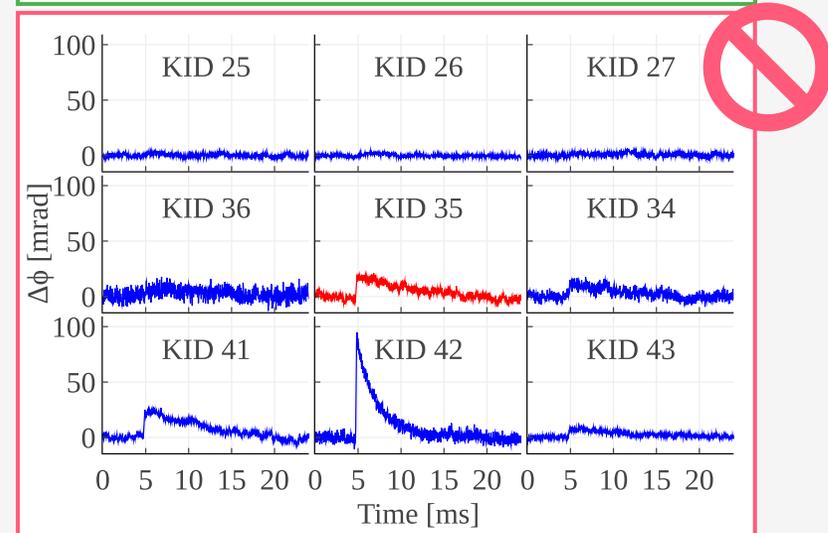
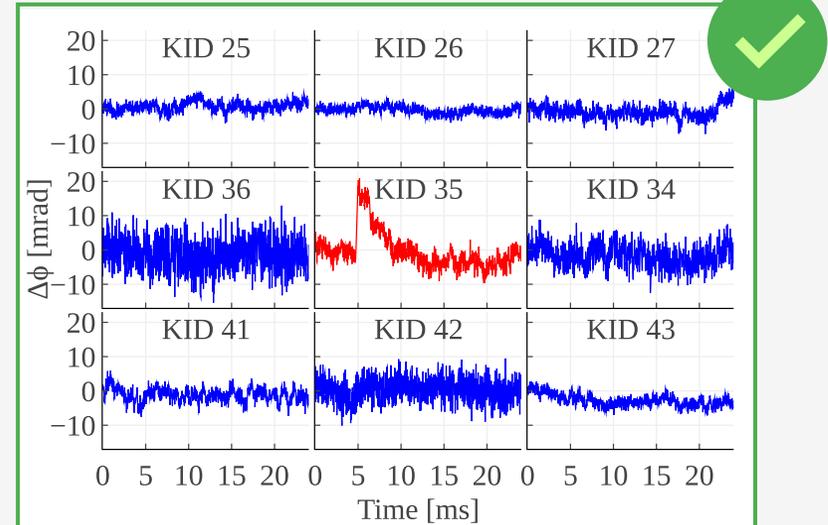
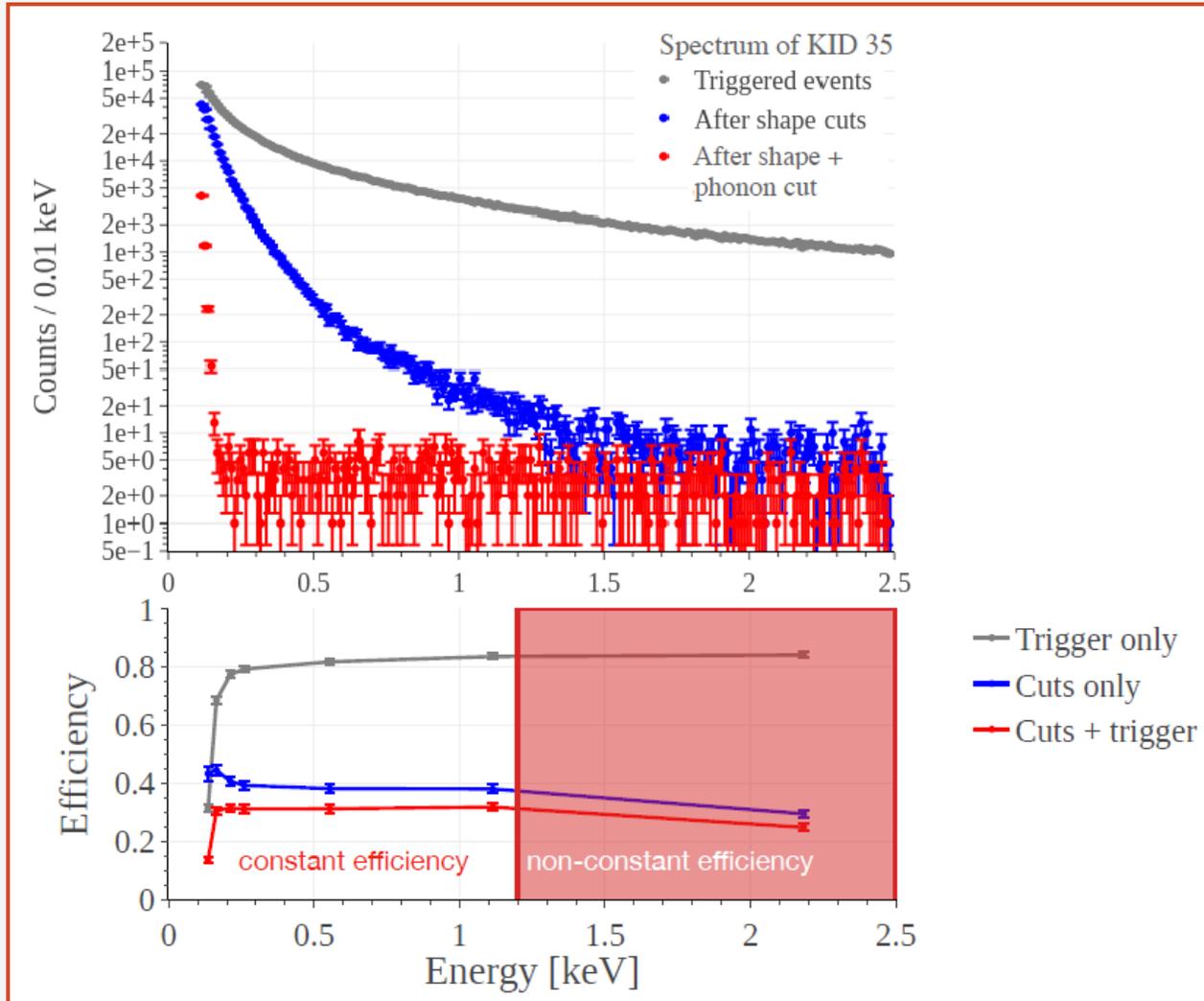
What do we need to investigate the spectrum further?

- **More simulations**
- More pixels per cluster?
- Better resolution of veto pixels
- Lower threshold (AlTiAl ready to test)
- More shielding

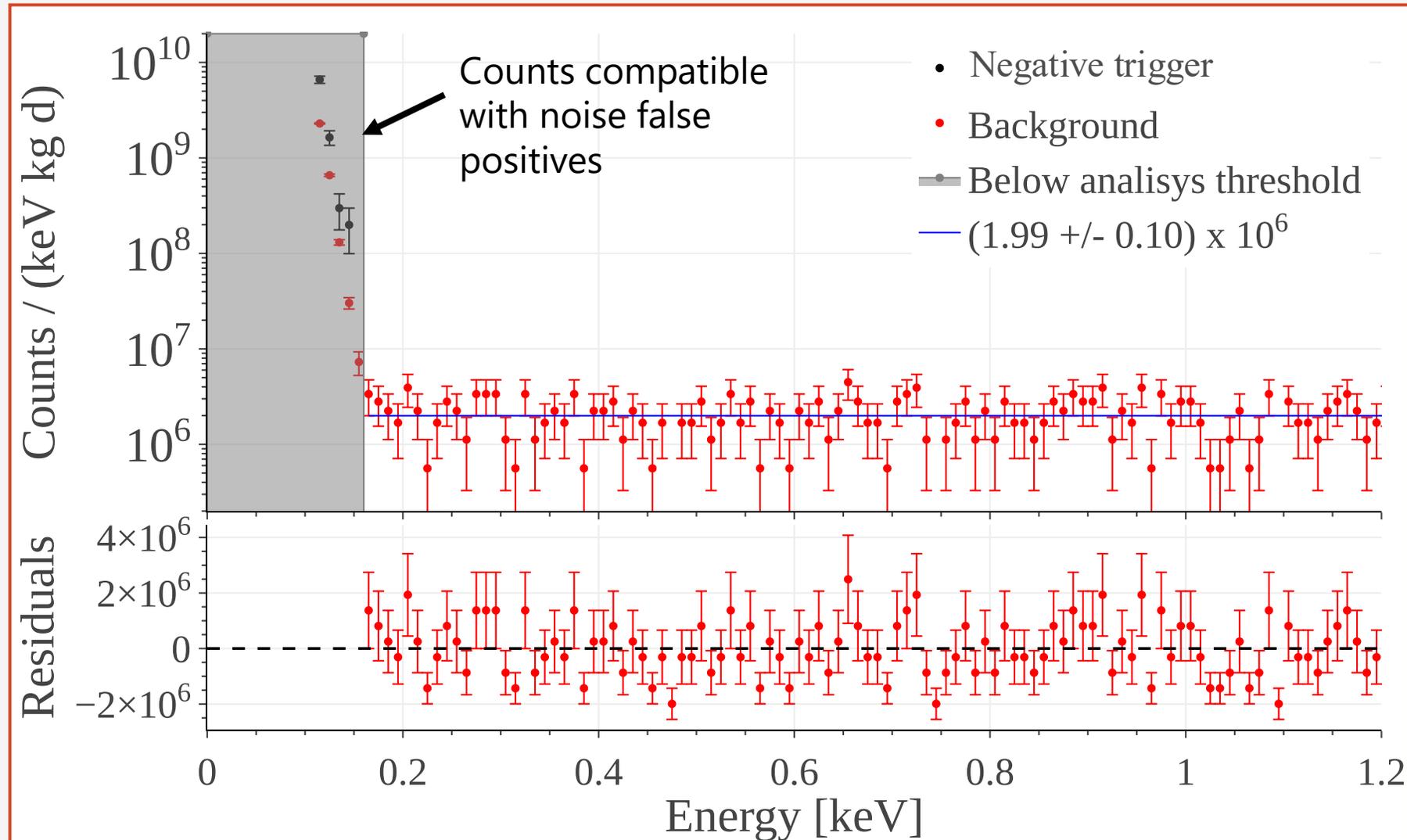


BACKUP SLIDES

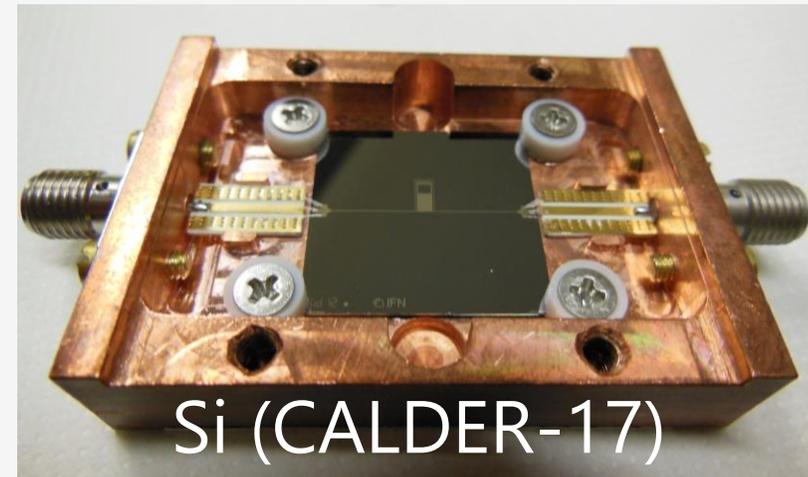
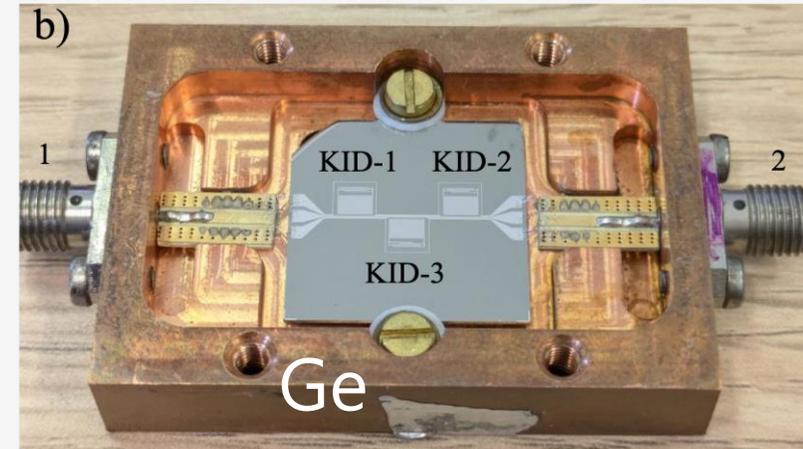
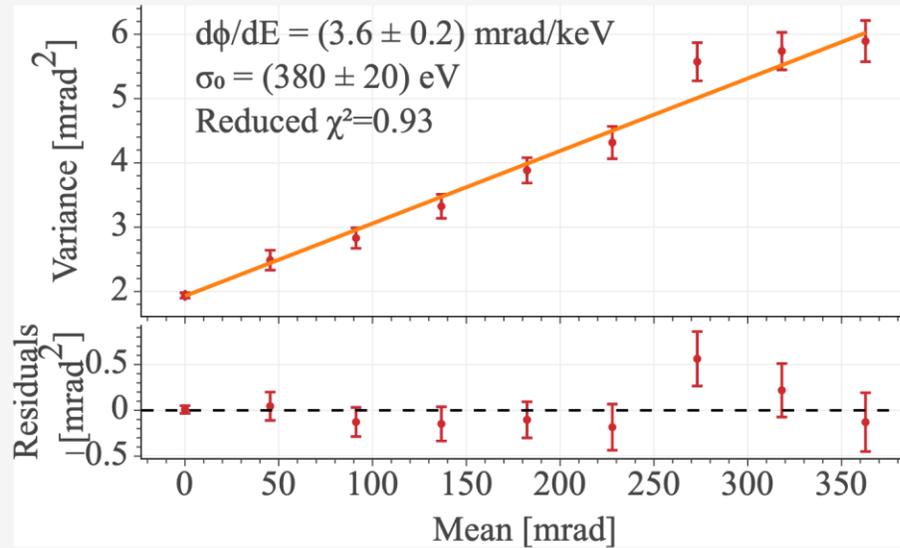
Background: pulse shape + phonon cuts



Background: result on surface @Sapienza U., no shield, 39 live hours

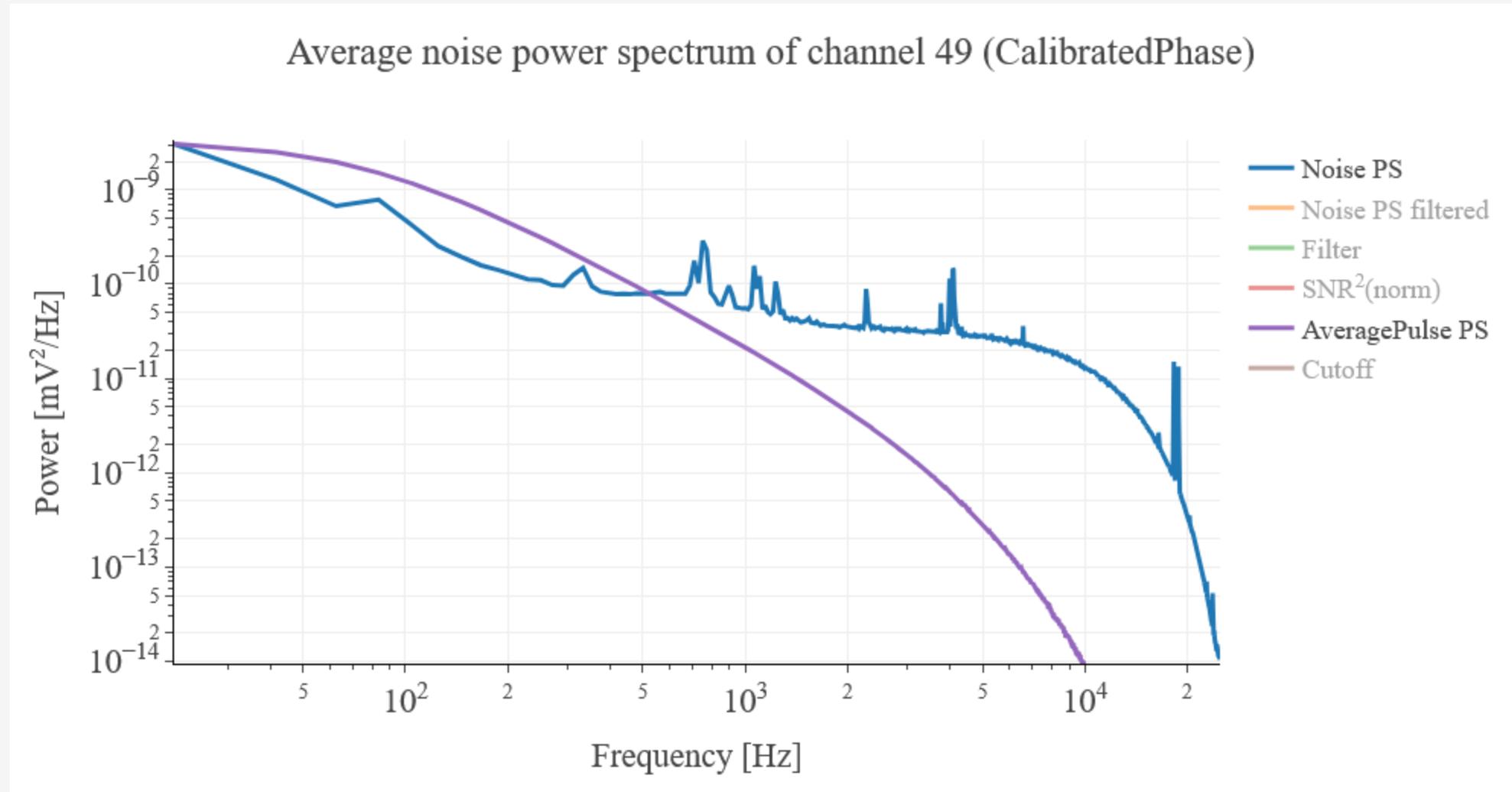


KIDs on Germanium for neutrino detection



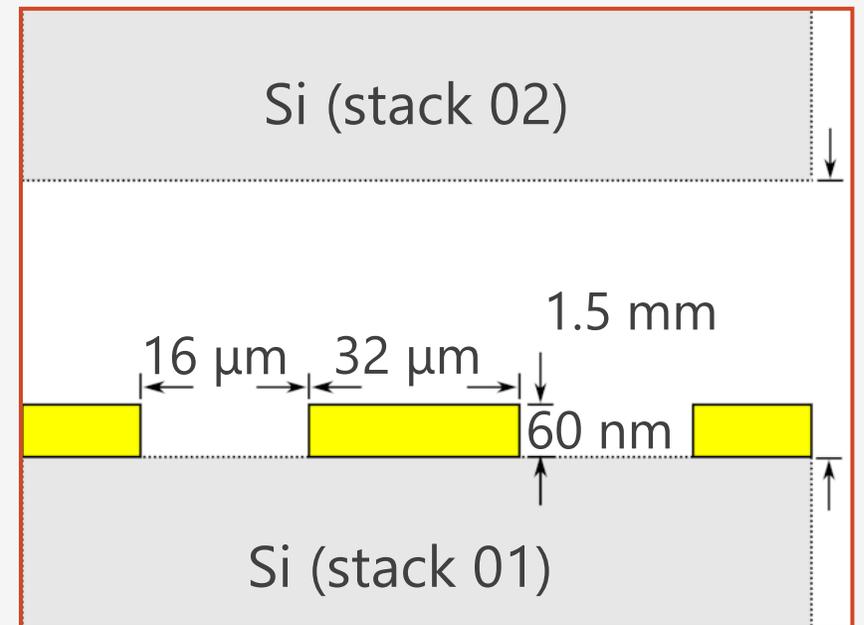
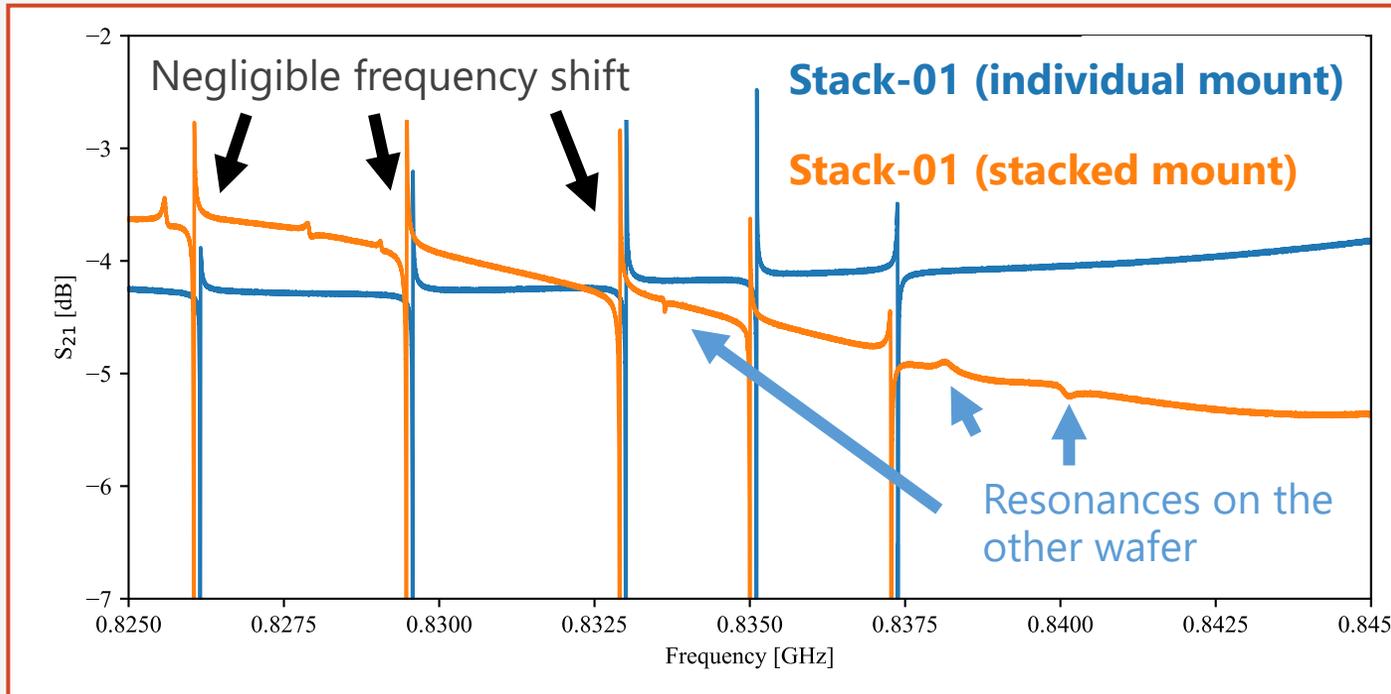
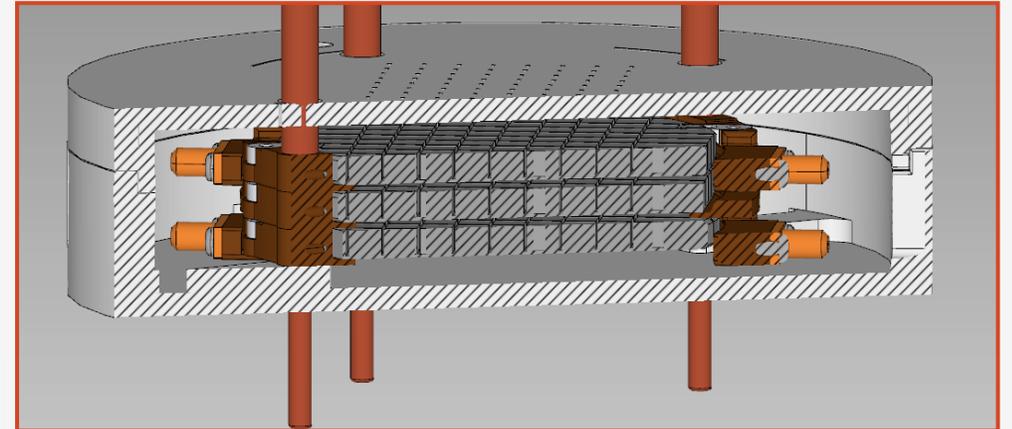
	$d\phi/dE$ [mrad/keV]	σ_0 [eV]	η [%]	$\frac{A_{\text{KID}}}{A_{\text{TOT}}}$
KID-1	3.6 ± 0.2	380 ± 20	2.0 ± 0.2	0.12
KID-2	2.5 ± 0.1	450 ± 22	2.0 ± 0.2	"
KID-3	2.2 ± 0.2	540 ± 31	1.6 ± 0.2	"
CALDER-17	5.8	115 ± 6	7.4 – 9.4	0.42

Pulse and noise power spectra



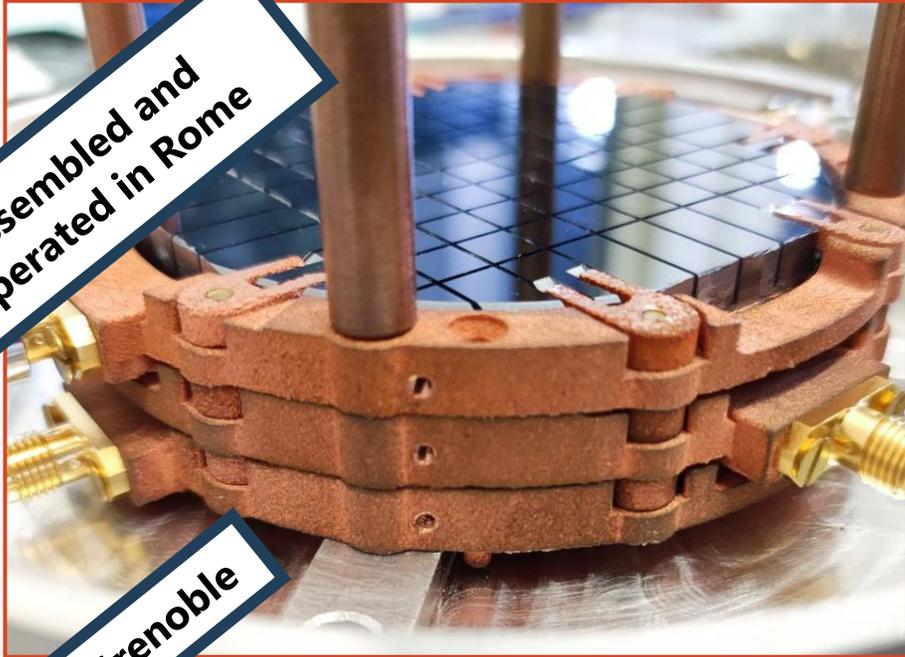
Status of the 3-wafer stack

- Holding structure: **thermalization** and mounting
- Reproducibility of the **electrical coupling**
- Reproduce the results of the unstacked wafers



Status of the 3-wafer stack

Assembled and operated in Rome

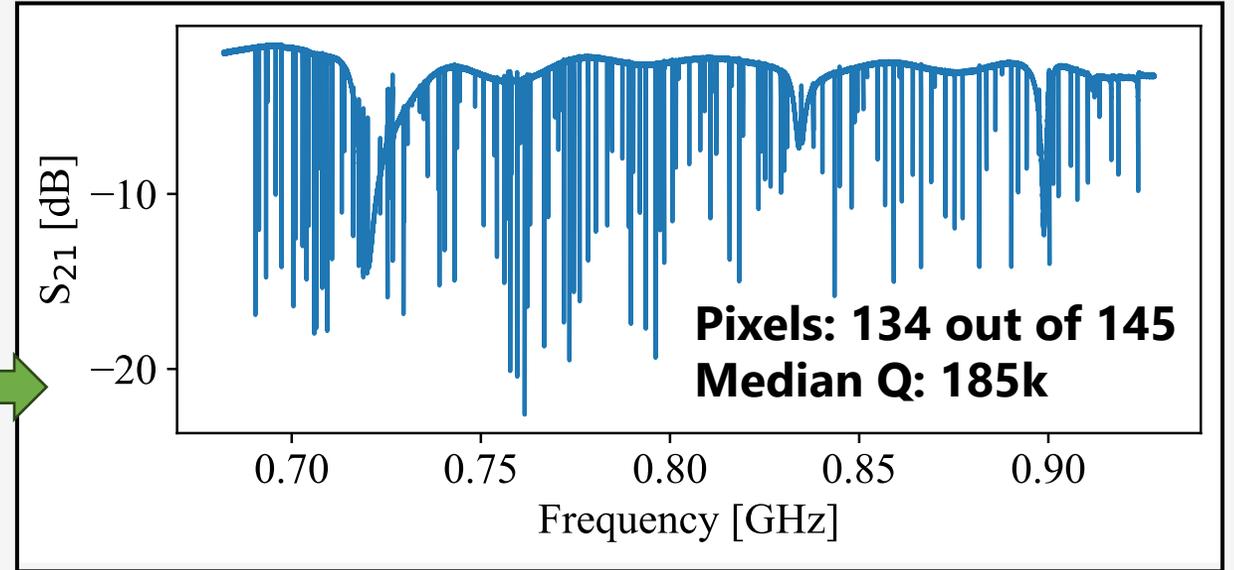
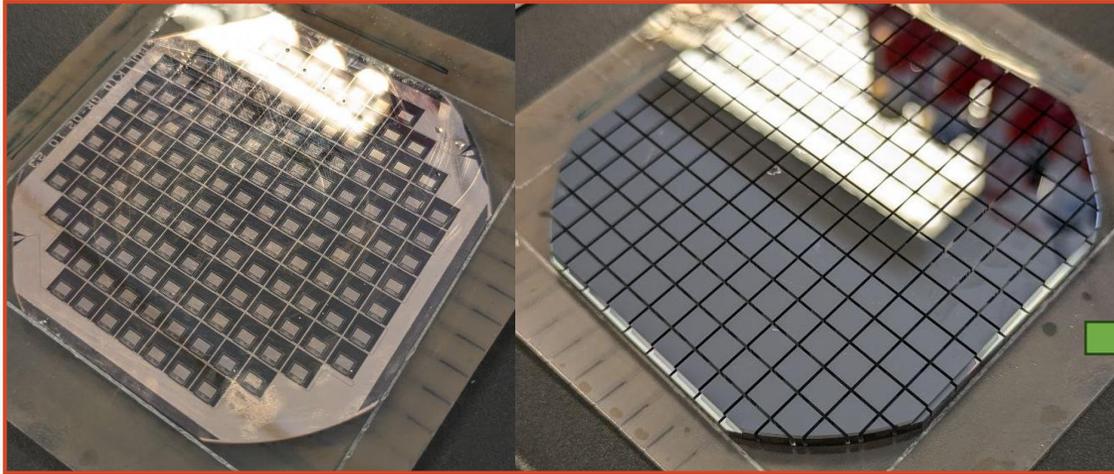


Fabricated in Grenoble

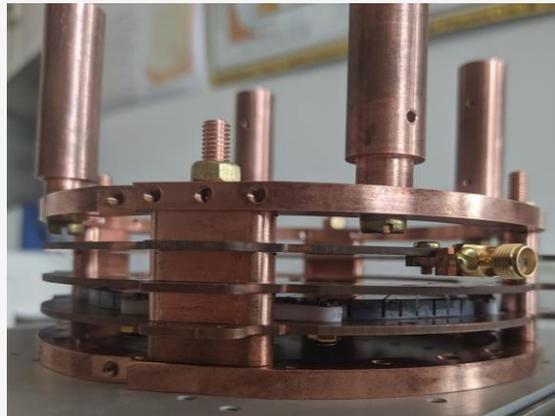
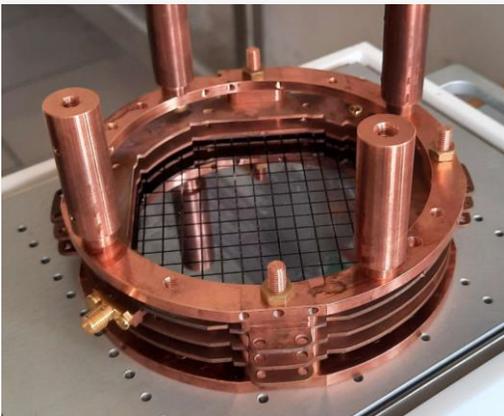


Stacked configuration with the **250 Kg lead castle shielding**

Scalability for the 100mm mask: thick wafer



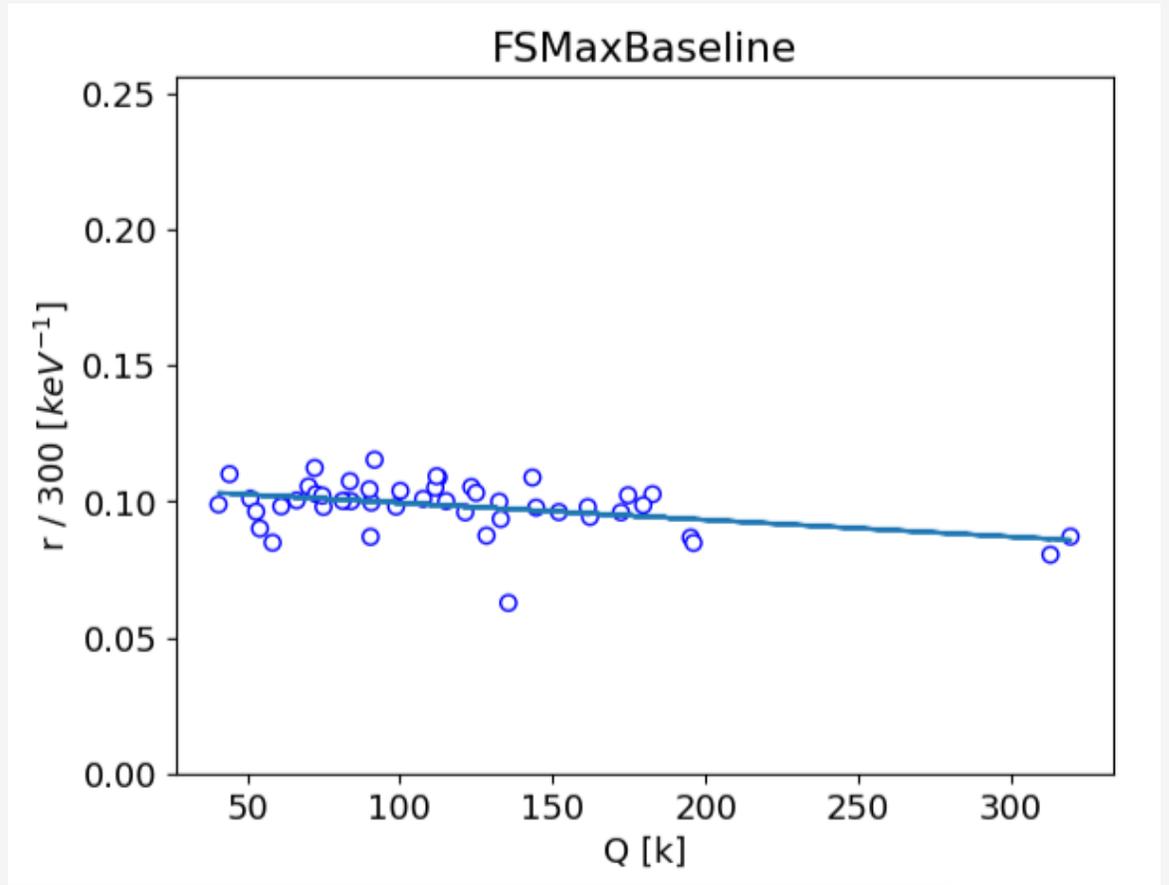
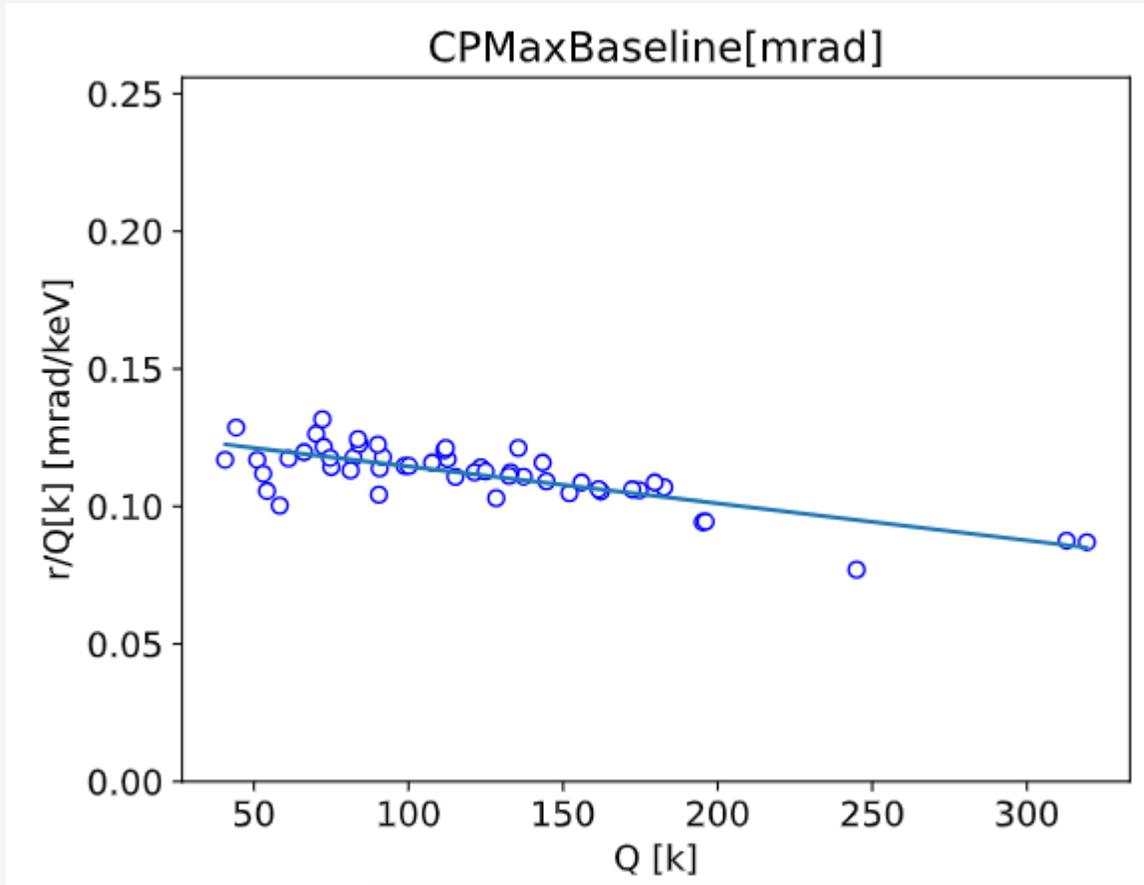
Assembly produced



Next steps:

- Series wafer production
- Lithography

Uniformity of wafer response to Americium source



Essentially same response to Am across the array

